



DESIGN OF ASICS FOR EXPERIMENTAL PHYSICS

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Plan

- ◆ Aim
- ◆ Trends in integrated circuit development
- ◆ Experience in establishing the ASIC design center
- ◆ Design center infrastructure
- ◆ Chip prototyping
- ◆ Design route and its main stages
- ◆ Example projects
- ◆ Conclusions and add-ins

Aim

to present:

- ◆ Trends in integrated circuit design (incl. rad-hard ones)
- ◆ Experience in establishing the ASIC design center
- ◆ Typical design routes and destination of their main stages
- ◆ Capabilities of Europractice for chip prototyping
- ◆ Example projects of ASICs

Trend: $N(x) = A \cdot \exp(t/\tau)$ $\tau \sim 18$ months

Integrated Circuit Complexity

Transistors
Per Die

10^{10}

10^9

10^8

10^7

10^6

10^5

10^4

10^3

10^2

10^1

10^0

◆ 1965 Actual Data

■ MOS Arrays ▲ MOS Logic 1975 Actual Data

● 1975 Projection

■ Memory

▲ Microprocessor

1K

4K

16K

64K

256K

1M

4M

16M

64M

128M

256M

512M

1G

2G

4G

4004

8080

8086

80286

i386™

i486™

Pentium®

Pentium® II

Pentium® III

Itanium

Page

Book

1 h audio

1 h video

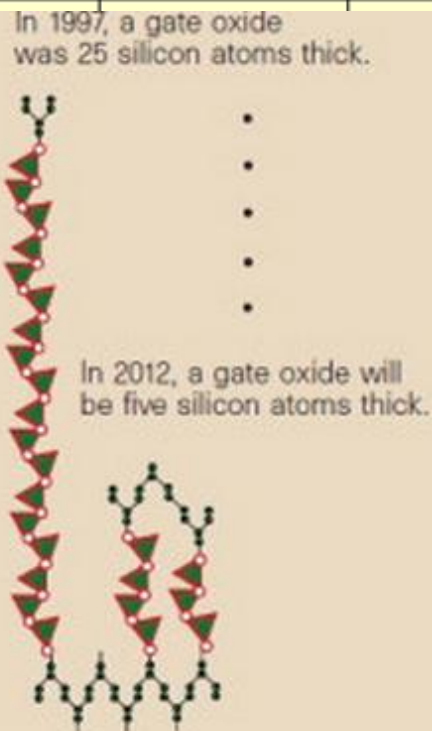
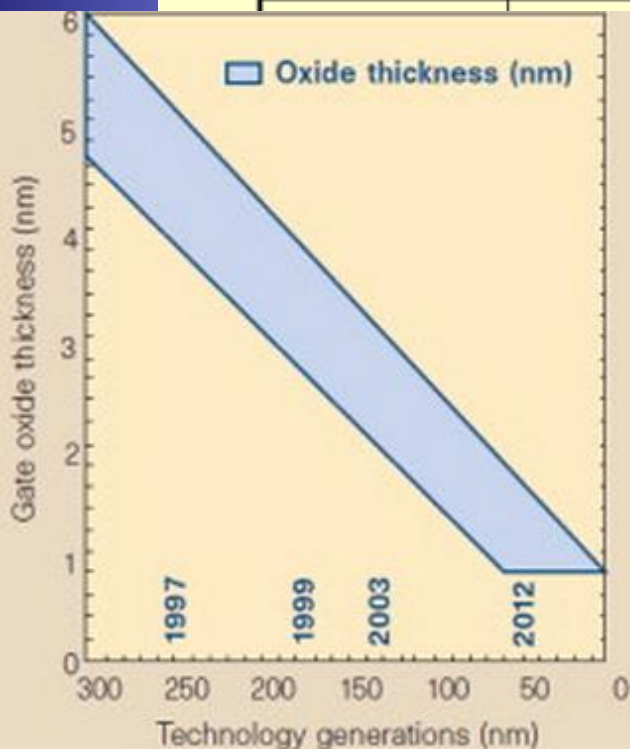
Moore Era

Up-to-date world-wide technologies

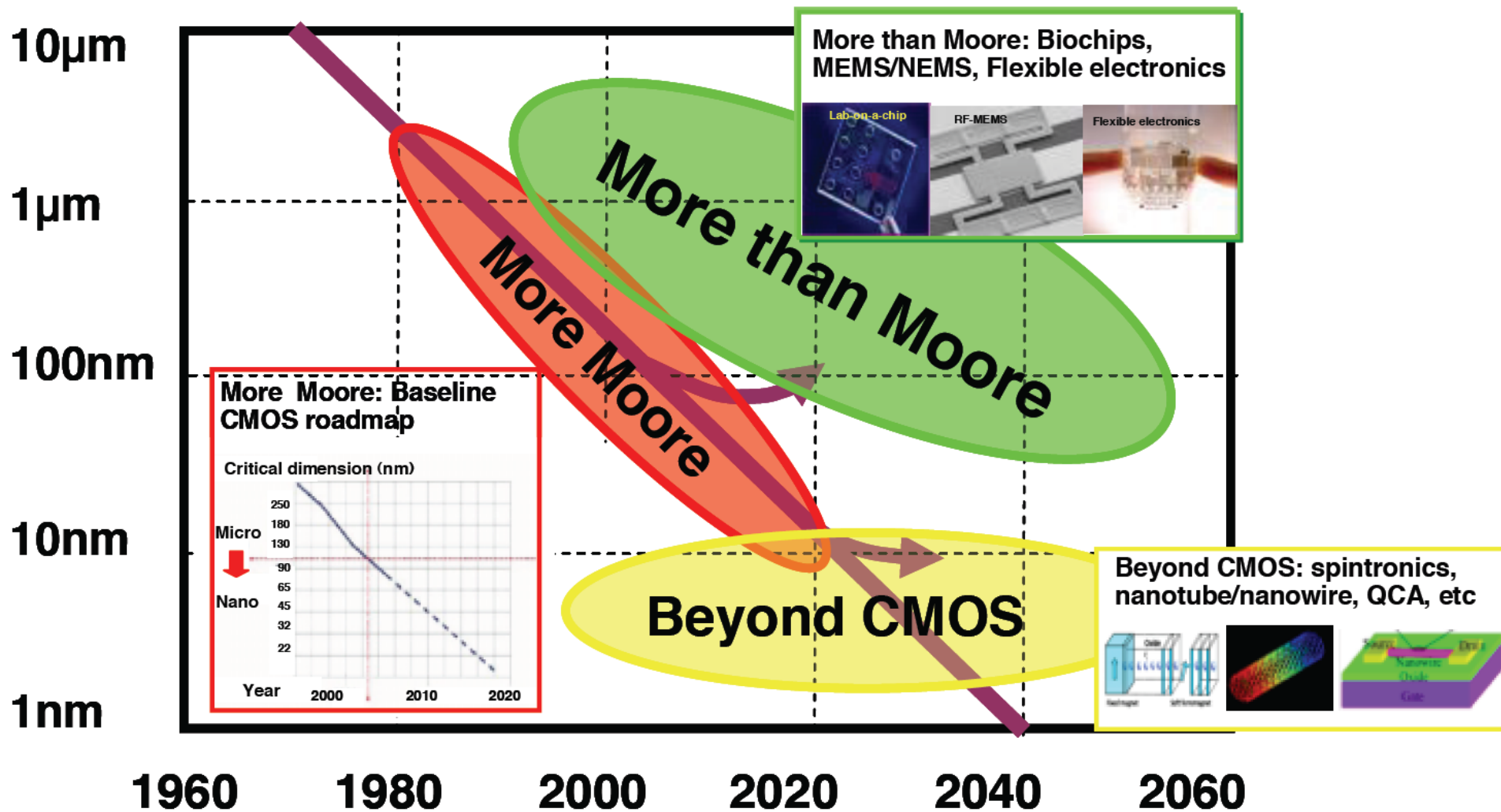


Roadmap

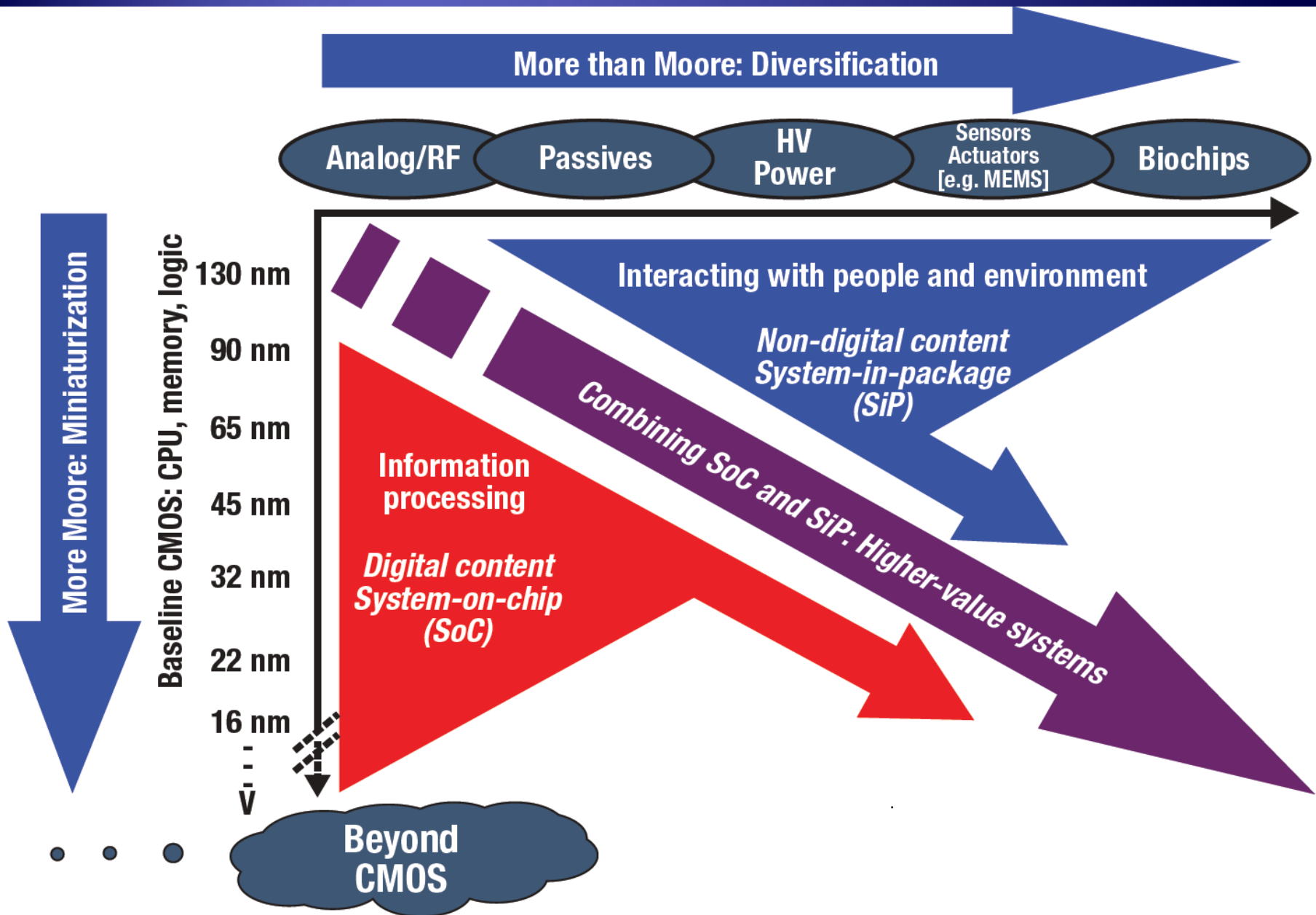
	2004	2007	2010	2013	2016
Technology Node [nm]	90	65	45	32	22
Transistor count [Mtr]			1500	3092	6184
			309	617	1235
					280
			15		53
			1.0	0.9	0.7
			54	32	22
			1024	1024	1024
					2048



Technology variety



More than Moore



Technological level in Russia

THE FEDERAL TARGET PROGRAM "DEVELOPMENT OF ELECTRONIC COMPONENT BASIS AND RADIOELECTRONICS" FOR 2008 - 2015

Approved by the Government on November, 26th, 2007, decree N 809

2 main target indicators:

– The **technological level** of modern electronic component basis is estimated, basing on the one of microelectronic products, mastered in manufacture

- **2008** → 0.18 μm

- **2011** → 0.09 μm

- **2015** → 0.045 μm

– There should be created 64 chip design centers in Russia

Important current tasks for Russia:

- A new Federal program on developing a chip design center network, comprising up to 150 centers, has been approved
- Creation of an advanced national photomask center

CMS

~1 000 000 custom chips (of 20 types)



Compact Muon Solenoid

ASIC development trends

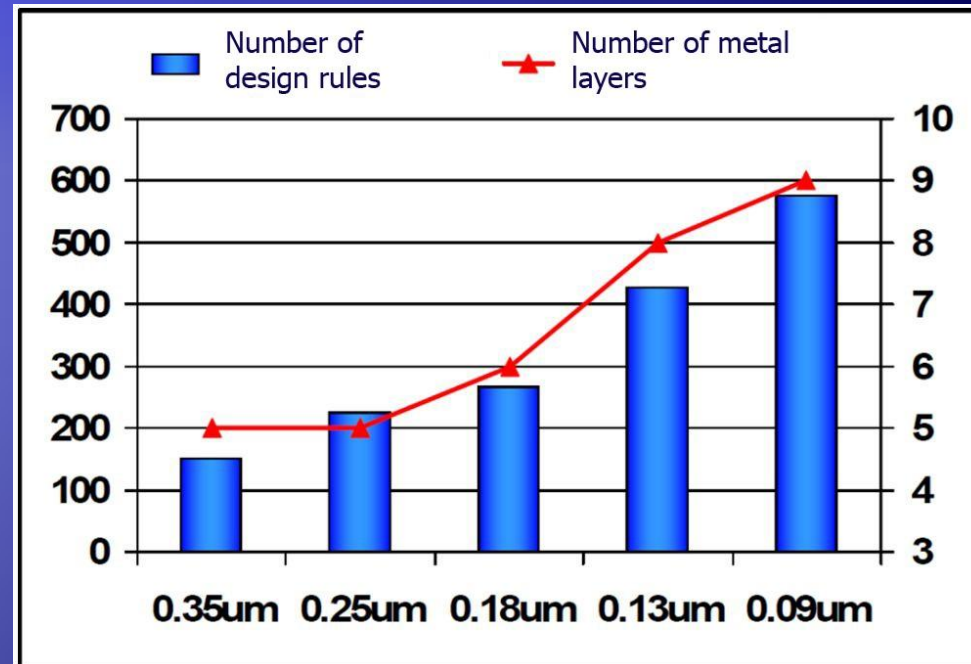
- ◆ The increasing quantity of elements at a simultaneous increase in their complexity and density. Moore law is still valid → **Increase in integration scale**
- ◆ **Digital signal processing** part more and more replaces analog one. (250nm → 10 K gates/mm² ... 28 nm → 3900 K gates/mm²)
- ◆ **Design cost** increase comparing to the one of manufacture
- ◆ Design **timeline** and number of prototype cycles (respins) are reduced
- ◆ For the majority of projects the minimum set of ASICs is to be developed in a one well verified technology (LHC → IBM 130 nm, SLHC → TSMC 130&65 nm, FAIR → UMC 0.18 μm) → **Standardization**

ASIC development trends (2)

- ◆ ASIC adaptation for other projects as criterion of economic efficiency → **Universalization**
- ◆ Functionality increase at a limited **power consumption** budget
- ◆ Increase in demand for a high technology (expensive) product. The accent at design is done at system (architectural) questions → **SOCs** (systems on a chip) dictate a **mixed-signal** character of design route
- ◆ The demanded number of ASIC wafers is small and can't interest a manufacturer (**10^6 channels** at ~ 100 chs/chip and ~ 1000 chips/wafer → **~ 10 wafers** only)

ASIC development trends (3)

- ◆ Design is based on the usage of constantly modernized:
 - 1) Computer Aided Design (**CAD**) systems (Cadence, Mentor Graphics, Synopsys, Agilent),
 - 2) technological libraries or **Design Kits** (elements, standard digital and IP blocks), including
 - 3) design **rules** of manufacturer, the quantity of which quickly grows for advanced technologies (> 2000 for 22 nm)
- ◆ Necessity of a fast and actually continuous **retraining** of experts
- ◆ Close **integration** of the design centers for both chip and system (hardware) level



Technology choice for FAIR

- ◆ Use technologies more and more advanced (with life time till 2017), but well characterized for design tools and having a reasonable cost → **UMC MMRF CMOS 0.18 μm** – main technology for FAIR (choice of 2004)
- ◆ Extremely compressed timeline for each cycle of custom design (4-6 months) and the presence of the necessary updated CAD tools at all levels of design
- ◆ Skilled staff of **young engineers** (till 2017)
- ◆ Start-to-finish (system level) design is necessary: Structural and behavioral modeling → Design of IP blocks at transistor level and that of systems at high-level language → Layout → Verification (ERC, DRC, LVS, PE, PS) → GDSII

Physics and MicroElectronics Integration

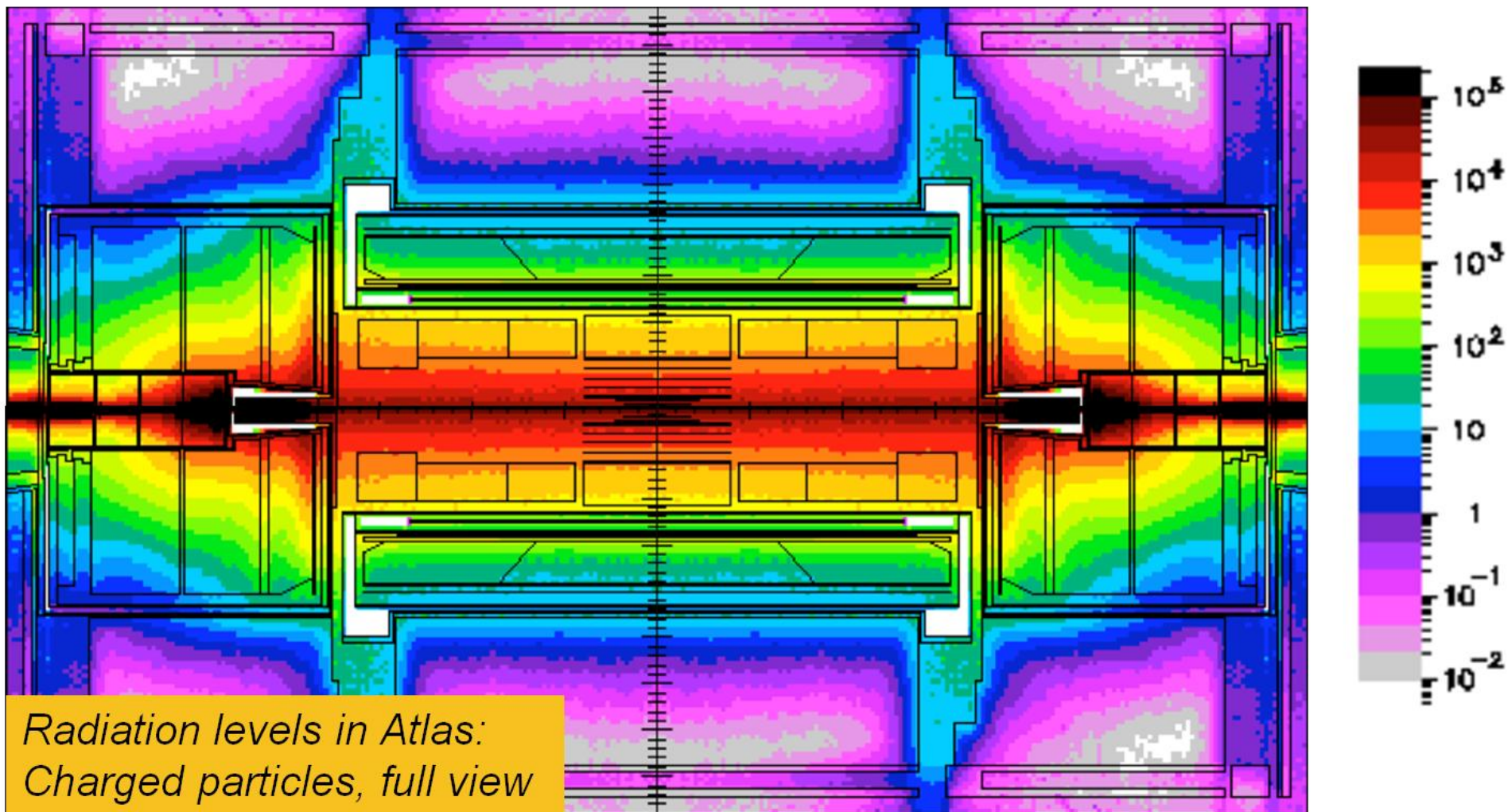


“Since long I have observed that Russian scientists have no access nor willingness to modern ASIC design for experimental physics”

H. Gutbrod (of 2011)

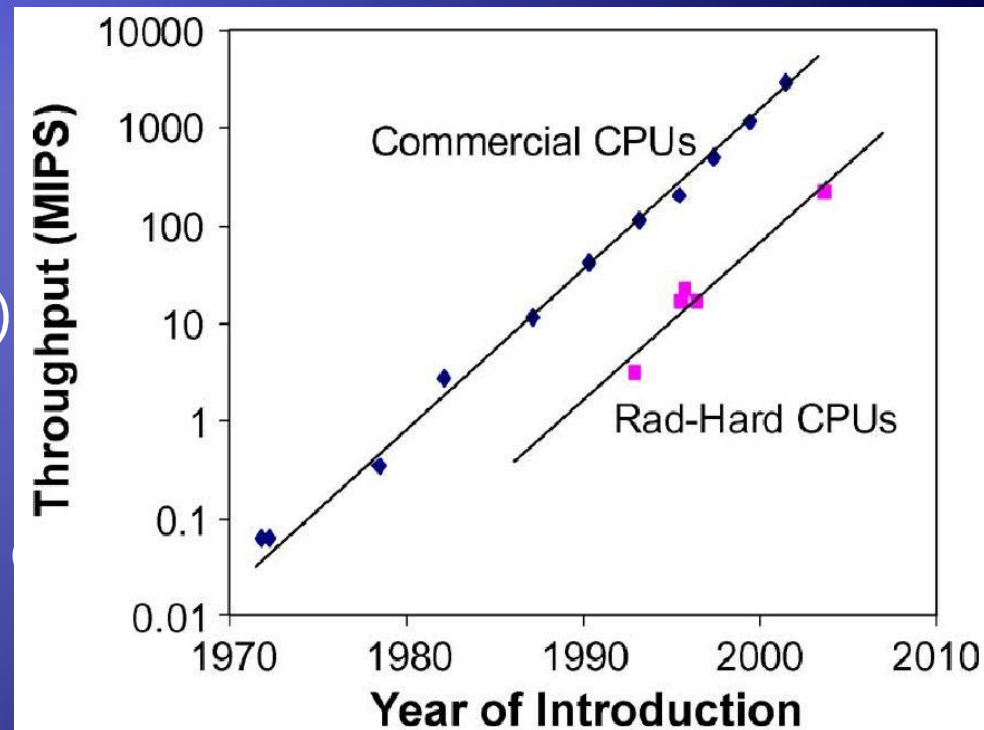
Co-director of FRRC

Radiation environment in ATLAS



Trends for radiation-hardened ICs

- Improvement of radiation hardness against total dose effects for new **commercial CMOS** processes. At the same time there is a wide spread of parameters among various manufacturers and no guarantee of long-term stability
- Radiation-hardness processes **lag behind** commercial ones for 5-7 years (more than three generations according to Moore)
- Radiation hardening of modern ASICs is provided by a wider usage of commercial and a refinement of different methods and means, used at early design stages (**rad-hard by design**)



R. Loebe, Improving Integrated Circuit Performance Through the Application of Hardness-by-Design Methodology IEEE Transaction on Nuclear science, v. 55, N4, 2008, p.1903-1925

Trends for rad-hardened ICs (2)

- Rad-hard technologies are **not** economically efficient. For them there exists only a small volume of orders
- Designer experience allows to carry out only a correct **choice** of the manufacturer, who can provide specific target requirements
- Active **investigation** of radiation **effects** for new bulk CMOS technologies and their **compiling** into the standard of design rules and CAD tools (Calibre, Assura, QRC, etc.) both at element and behavioral levels

Short summary on rad-hard ASICs

- A number of rad-hard applications will demand the design of rad-hard components and their manufacture in a **radiation hardened technology** to meet rigid requirements. The part of such ASICs will be decreased each year
- Continuous improvement of very complex rad-hard systems will critically depend on the introduction of commercialized microelectronic innovations in these systems
- Raising the limiting complexity of these systems to the level, reached in commercial technologies, will demand a shift of many projects in the direction of creating **radiation-tolerant** components, using traditional commercial technologies, applying the methods of maintaining an acceptable radiation hardness

Actual task – analytical comparison of technologies by the radiation hardness:

- ◆ 1) Industrial (commercial) CMOS technology with use of methods “rad-hard-by-design”
- ◆ 2) Rad-hardened technology, according to the Moore law, lags more than 3 generations behind the commercial CMOS one

Thus, the practical dilemma is:

What is better

either a rad-hard 350 nm process
(for example, silicon-on-isolator)

or

a bulk CMOS 130 (90) nm process?

Traditional methods for radiation hardening

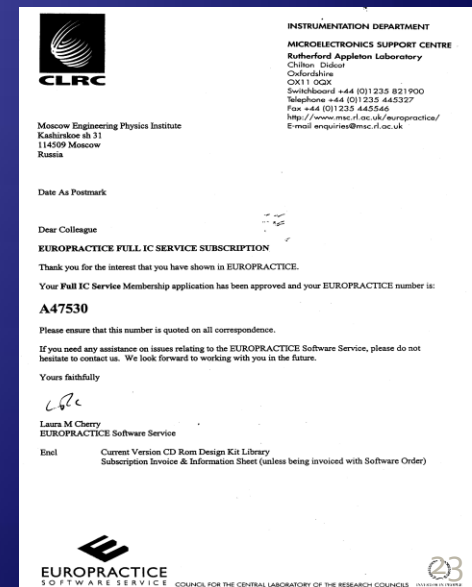
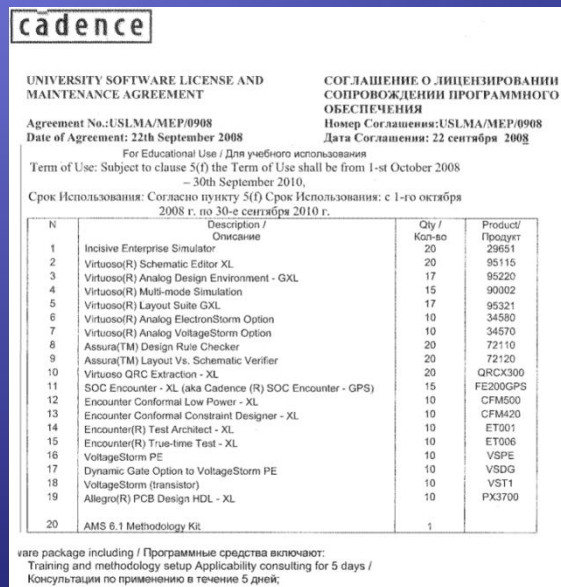
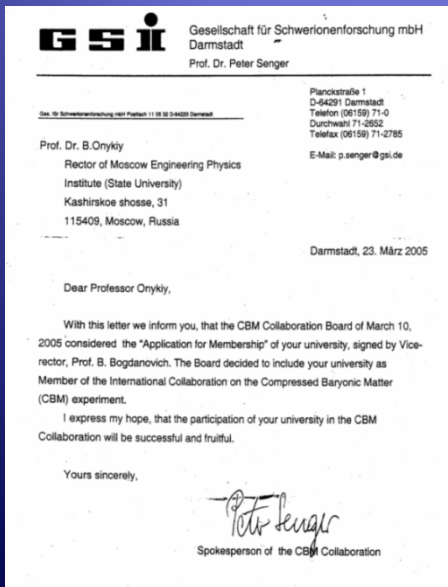
- ◆ Circuital (reservation, redundancy, coding, adaptive biasing and & so on)
- ◆ Layout (guard rings, ring transistors, and so on)
- ◆ Technological (low volume CMOS, SOI, trench isolation, & so on). The required rad-hardness level is provided by a semiconductor structure choice and use of the special technological processes

Rad-hard by design concept

- ◆ **Refinement** of traditional non- rad hard libraries for CAD
- ◆ **Elaboration** of additional **design rules**, improving rad-hardness at the following 3 levels of design:
 - 1) Transistor level
 - 2) Level of cells, gates and IP blocks
 - 3) System level
- ◆ Creation of calibrated **test structures** and expansion of the scaled element libraries
- ◆ Monitoring and statistical analysis of the ASIC rad-hard **stability**, provided at manufacture
- ◆ Rad-hard tests of chips at both **passive and active work modes**

Backgrounds for an ASIC design center in MEPhI

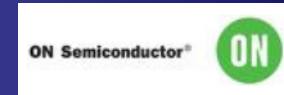
- 1) Now MEPhI is the **National Research Nuclear University – NRNU MEPhI**
- 2) The **experience** on chip design in joint research projects with leading RF enterprises
- 3) Full membership (A47530) in **Europractice** since 2003
- 4) Participation in a number of **International** physical experiments (incl. ATLAS, ALICE in CERN and CBM at FAIR)
- 5) Starting from 1996 MEPhI has direct **licensed agreements** with Cadence, Mentor Graphics, Synopsys, Agilent



Europactice

offers at a reasonable price:

- ♦ licensed **CADs** of world leaders
- ♦ access to design rules and technological libraries (**design kits**) for a number of nanometer and submicron (40 nm ... 0.8 μm) processes, including SiGe, SOI, A_3B_5

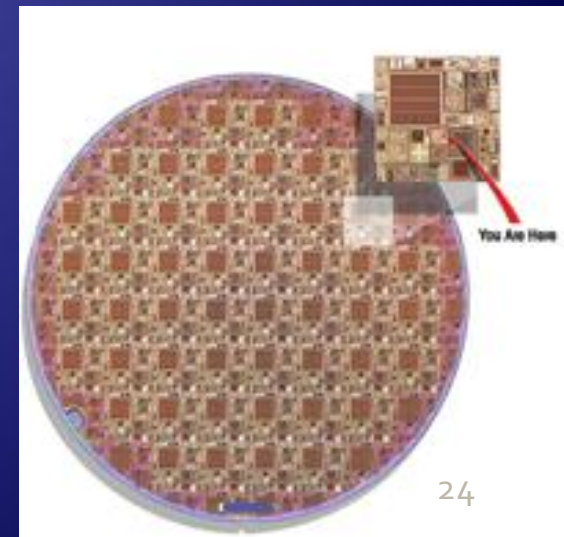


- ♦ access to **microsystem and MEMS technologies**



provides an inexpensive (**360...7900 Euro/sq.mm**) prototyping of ASICs via advanced processes (down to **40 nm** CMOS) using the so called multiproject approach, when the wafer cost is shared among projects of many customers

since 2013 Europactice provides **discounted pricing** for Russia as well as EU



The EURO PRACTICE IC Manufacturing and Testing Service (ASIC Service) is coordinated by IMEC and offers industry and academia a fully supported, low-cost route to ASIC design, prototyping and low-volume manufacturing.

SERVICES

- Low-cost prototyping service on regular Multi-Project Wafer (MPW) runs
- Low-cost, low-volume service (up to millions of devices)
- A wide range of IC-technologies, down to 30nm (CMOS, SiGe, SiGeC)
- Low-volume price estimation service
- Design and electrical rule checking on every submitted design
- Packaging service offering a wide range of ceramic and plastic packages
- Prototype and volume testing
- Customer interface with a Single Manufacturing Center of choice (see below)
- Easy-to-use design and/or integration process via WWW
- Cell libraries & design kits available

- [illegible]

gemetal + MPW runs including minimax conditions (*) = only minimax runs

Serviced by:
I IMEC
F Fraunhofer I

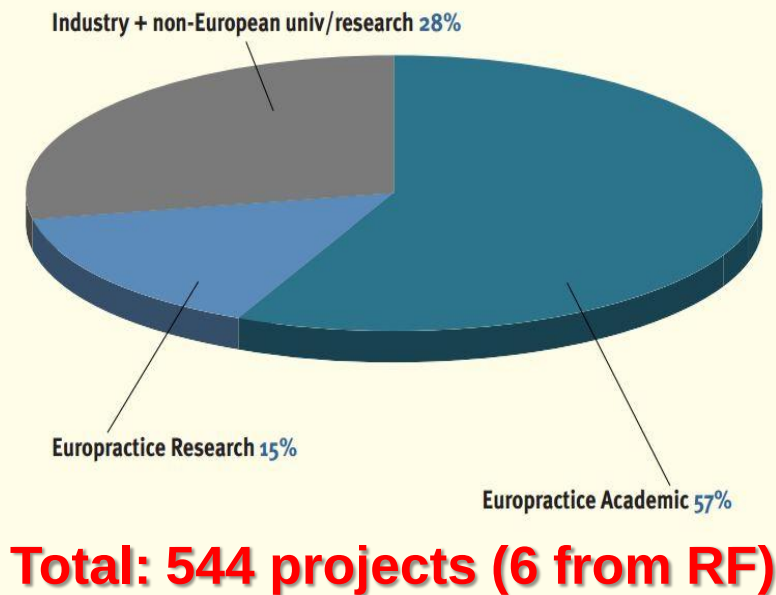


EUROPRACTICE
ASIC SERVICE

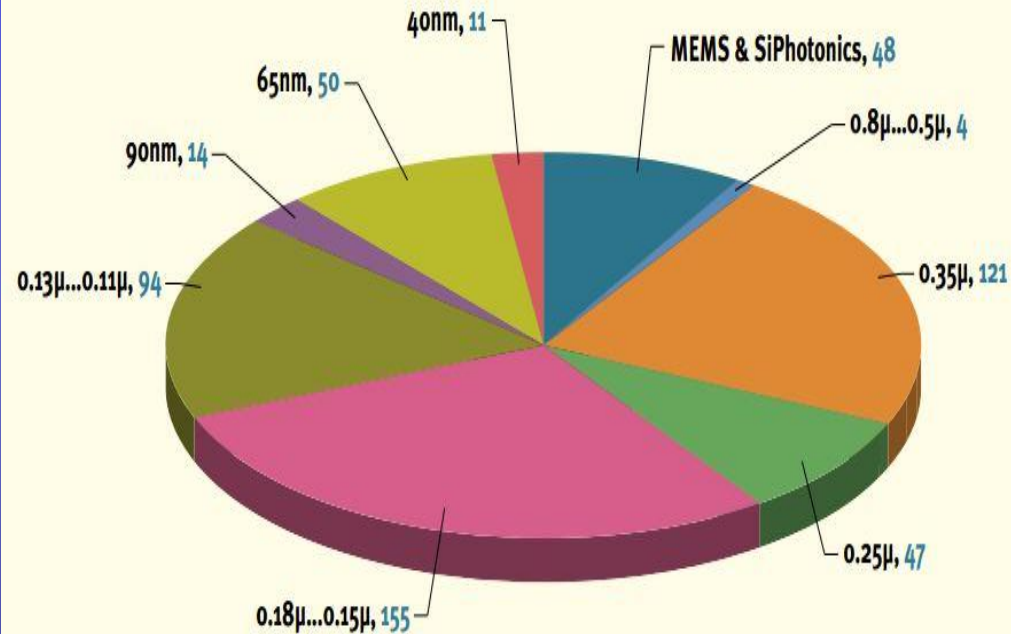


http://www.europpractice-ic.com/docs/EP_wall_calendar_2014.pdf

Number of ASIC projects, manufactured via Europractice *



MPW designs in 2014



MPW designs in 2014: technology node and number of designs

* Europractice annual report 2014,
www.europractice-ic.com/docs/Annual_report_2014.pdf

Number of **RF** ASIC projects, manufactured via Europractice *

Russia

Budker Institute of Nuclear Physics	Novosibirsk	3
IPMCE	Moscow	3
JSC “NTLAB”	Moscow	2
Moscow Institute of Electronic Technology	Moscow	5
Moscow Institute of Physics and Technology	Moscow	5
Moscow Engineering Physics Institute	Moscow	17
N.I. Lobachevsky State Univ	Nizhni Novgorod	8
SRIET-SMS CJSC	Voronezh	6
University St Petersburg	St Petersburg	5
Vladimir State university	Vladimir	1

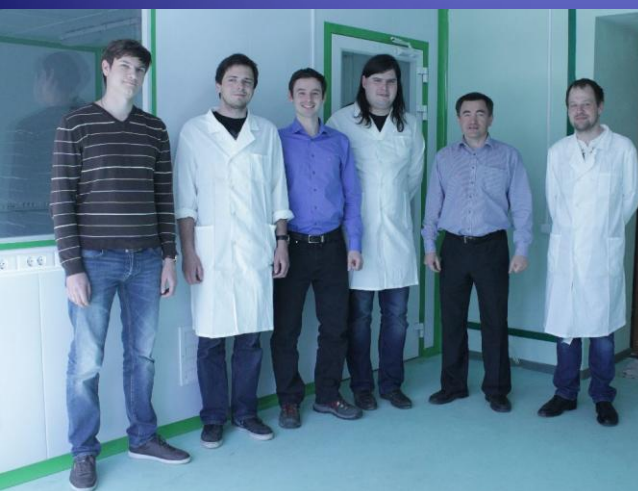
ASIC Lab tasks

The infrastructure is financed since 2013 by a grant given by the Russian Federation Government based on resolution **№220**. The head of Lab is V. Samsonov

- Development Russian design center of Application Specific Integrated Circuits with technological nodes of 40-180 nm.
- Design of ASICs for well recognized International and Russian experiments (for ex. CBM, NIKA)
- Development of competence center on chip design. Organizing topical Conferences, Workshops, Master classes.
- Research of new project solutions, test prototyping and small volume production

Infrastructure of the ASIC design center

- distributed interdepartmental **1 Gb/s** local Intranet
- clusters of network SUN and Linux **workstations** in a number of departments
- licensed microelectronics tools for computer aided design – **Cadence, Mentor Graphics, Synopsys, Agilent**
- **computer classes** for core students
- technological libraries starting from **45 nm**



Organization of All-Russia Workshops

- Учебно-методический семинар (AMS Methodology Kit Workshop) компании Cadence

22-24 сентября 2009 г.

- II Всероссийский учебно-методический семинар по проектированию аналого-цифровых микросхем

10 - 14 октября 2011 г.

- Всероссийская молодежная научная школа «Современные средства автоматизированного проектирования смешанных (аналого-цифровых) интегральных микросхем для аппаратуры физического эксперимента»

11 - 14 сентября 2012 г.

Partners:



cādence

Organization of All-Russia Workshops (2)

- IV Всероссийский научно-методический семинар по средствам проектирования интегральных микросхем для аппаратуры физического эксперимента

29-31 октября 2013 г.

- V Всероссийский научно-методический семинар по автоматизированному проектированию интегральных микросхем для физического эксперимента

8-11 декабря 2014 г.

Partners:



cādence

2012 event photo





2013 event



IV Всероссийский научно-методический семинар по средствам проектирования интегральных микросхем для аппаратуры физического эксперимента

29-31 октября 2013 года

Приглашаем вас принять участие в работе семинара.

Семинар организован НИЯУ МИФИ при поддержке Минобрнауки РФ (в рамках мероприятий по Постановлению Правительства РФ №220), американской компании Cadence Design Systems (www.cadence.com) и Центра ФАИР-Россия (ИЦФР, ftrc.itep.ru).

Цель семинара - познакомить участников с методологией автоматизированного проектирования смешанных (аналого-цифровых) интегральных микросхем, развиваемой компанией Cadence, и провести практические мастер-классы с целью популяризации микроэлектронных САПР для предприятий высокотехнологичного сектора экономики РФ. Приоритет будет отдан предприятиям ГК "Росатом", осуществляющим крупные проекты, такие как на международных ускорителях ФАИР (г. Дармштадт, Германия) и НИКА (г. Дубна).

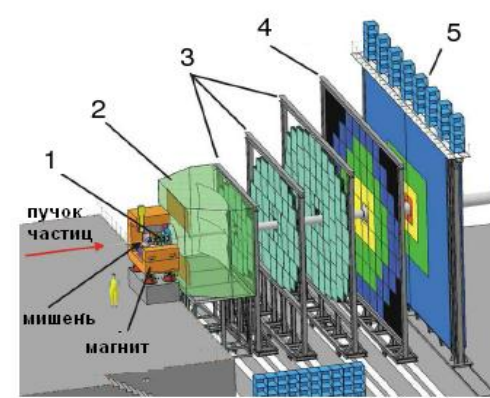
Важная часть семинара - тематические лекции приглашенных известных в мире ученых из CERN (Женева), GSI (Дармштадт), AGH (Краков), отражающие последние мировые достижения в области реализации и внедрения сложнофункциональных интегральных микросхем для аппаратуры физического эксперимента.

Более подробная информация представлена на сайте: cad.mephi.ru.

ASIC projects

- 128-channel prototype ASIC for data-driven read-out of CBM STS

0.18 μm CMOS UMC (Taiwan), consumption 2 mW/ch., shaping time 100 ns, structure 128→16/ Chip contains preamplifier, shaper (filter), comparators, cross-point switch, peak detectors, 9-bit ADC and so on



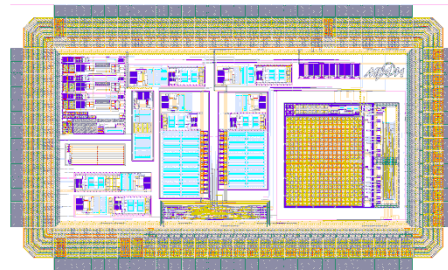
- Smart sensor readout ASIC (Rosatom)

0.35 μm SiGe BiCMOS AMS (Austria), temperature range -55...+80 °C, consumption 3 mW. Chip contains instrumentation amplifier, 14-bit ADC, two 14-bit DAC, references, electronic thermometer and so on



- 32-channel ASIC for “Nucleon” project (Roscosmos)

0.35 μm CMOS AMIS/OnSemi (Belgium), dynamic range 100 pCb, consumption 2 mW/ch., multiplexed (serial) output

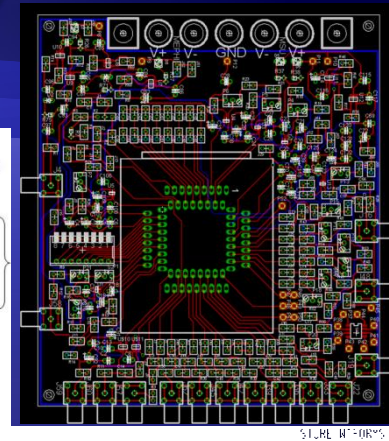
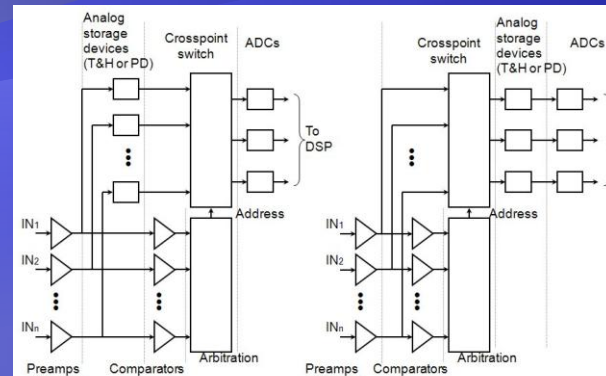
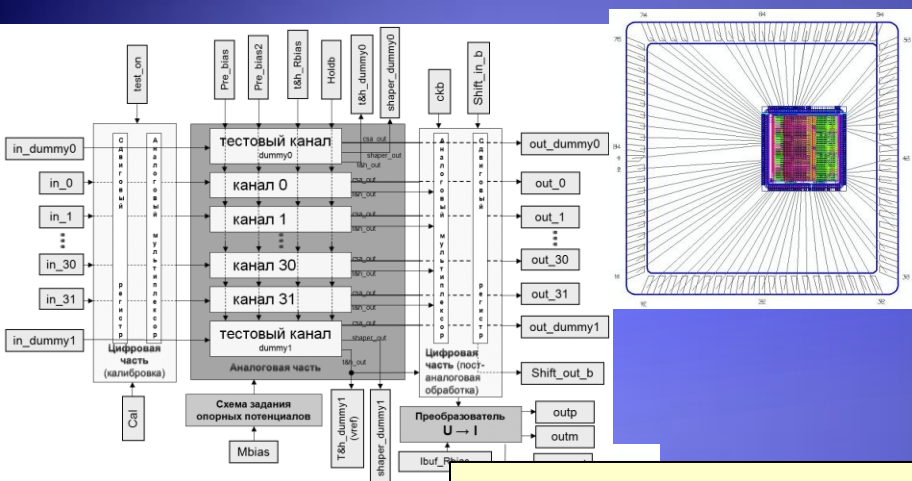


- IP blocks for system on chip, controlling a new aircraft engine (Ministry of Education and Science)

0.18 μm CMOS UMC (Taiwan), consumption 10 mW/ch., 9-bit ADC

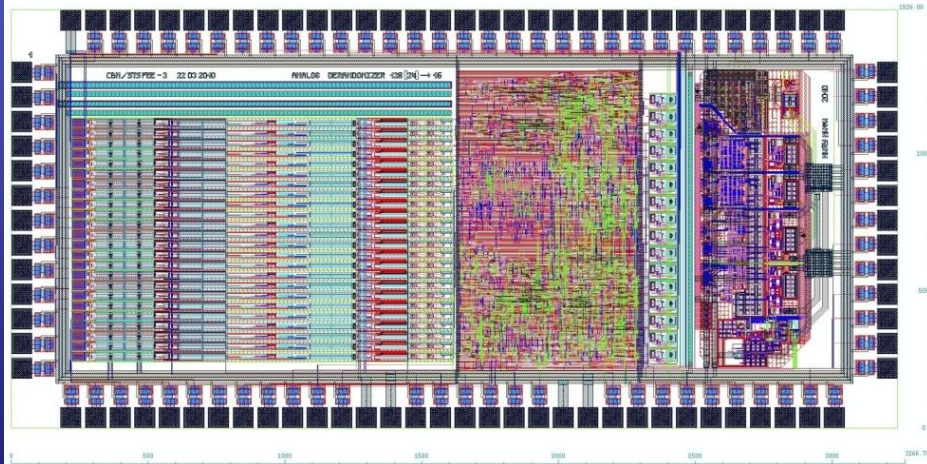
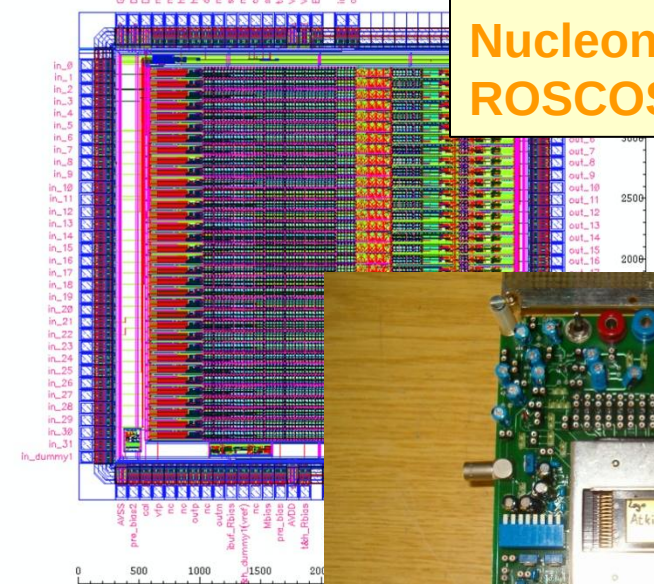
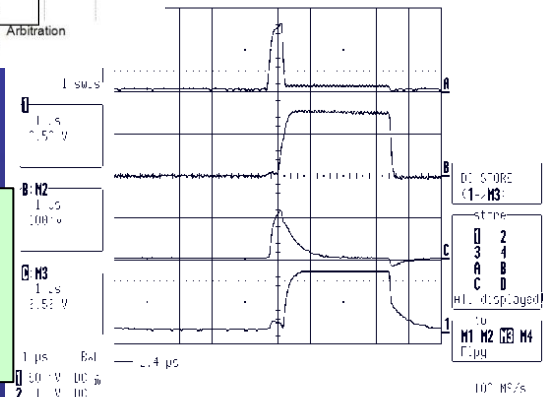


SOME DETAILS OF ASIC PROJECTS



32-channel ASIC for Nucleon project of ROSCOSMOS

128-channel prototype ASIC for CBM STS

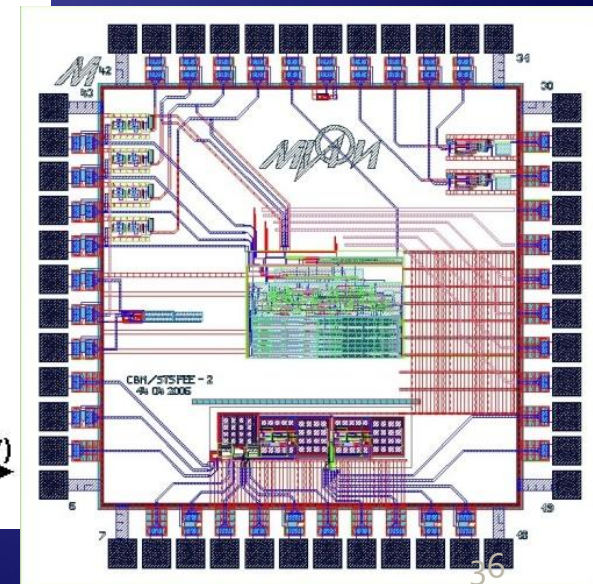
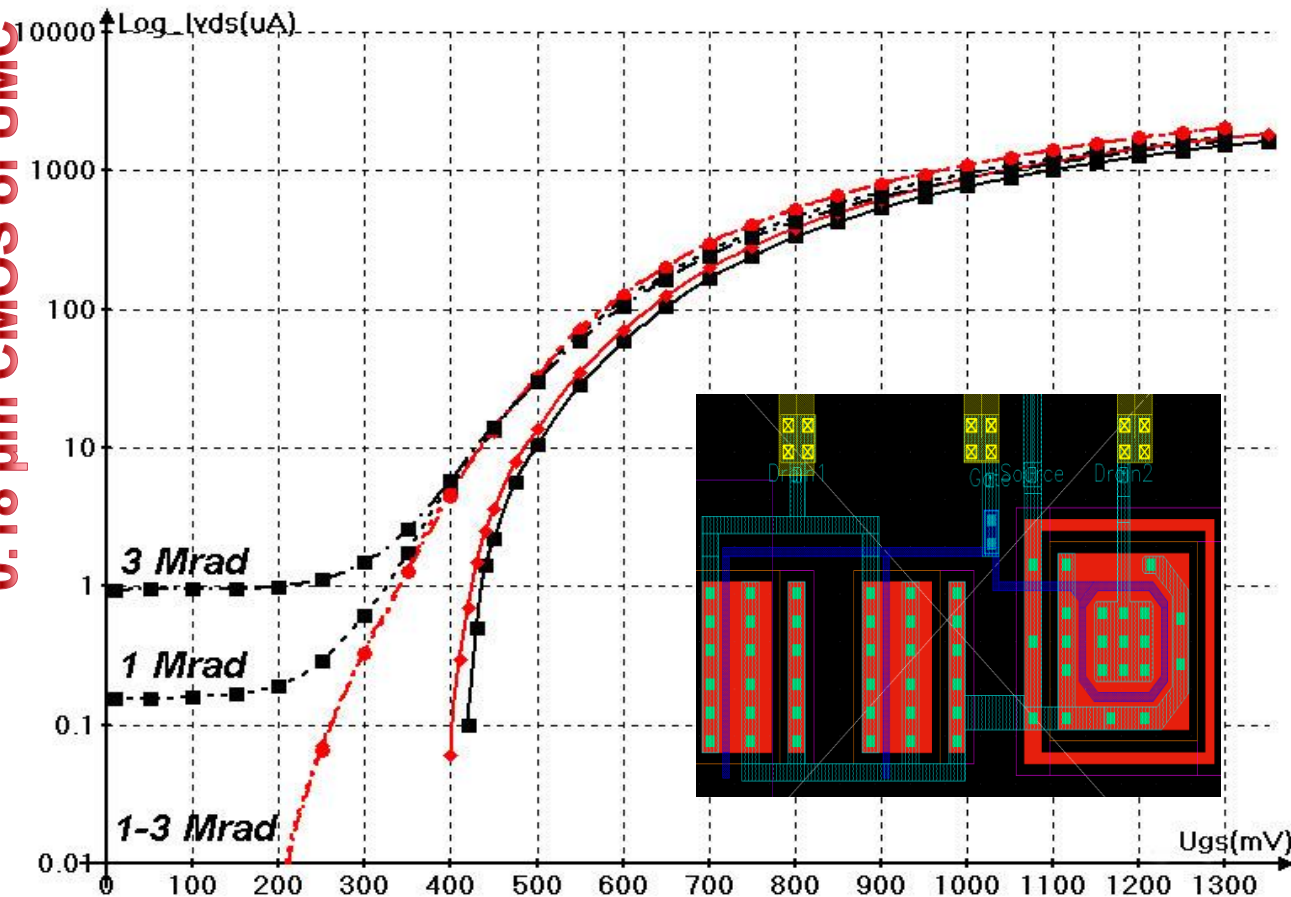


Tests for total dose effects

($E=8\text{ MeV}$; $F=10^{11}\text{ e/cm}^2\text{ s}$; $D=0.1; 1; 3\text{ Mrad}$)

- 1) Threshold voltage shift ($\sim 100\text{ mV}$);
- 2) Leakage currents --- standard (strip-like) nMOS;
--- ring transistors

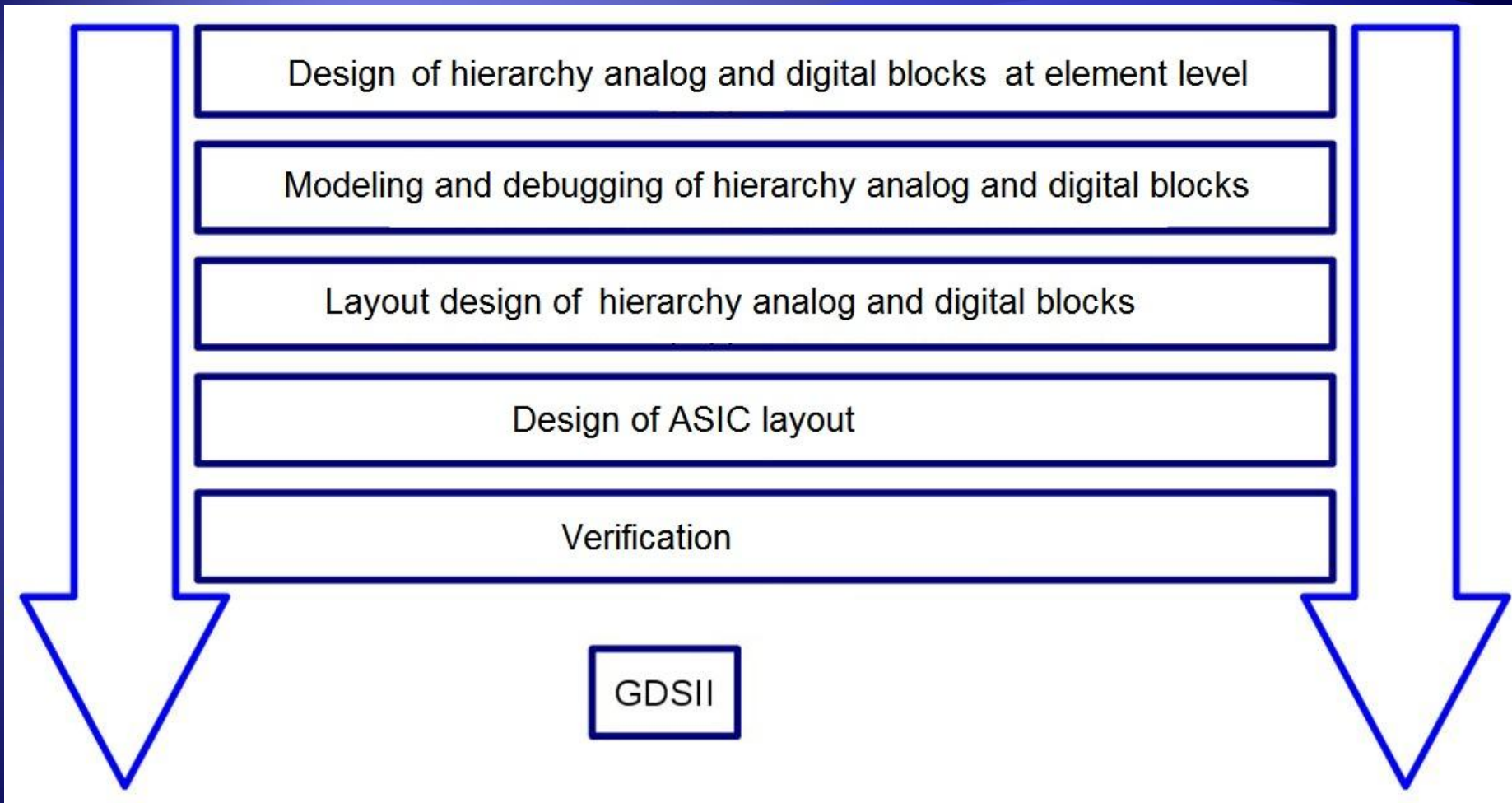
0.18 μm CMOS of UMC



5 design phases for ASIC development

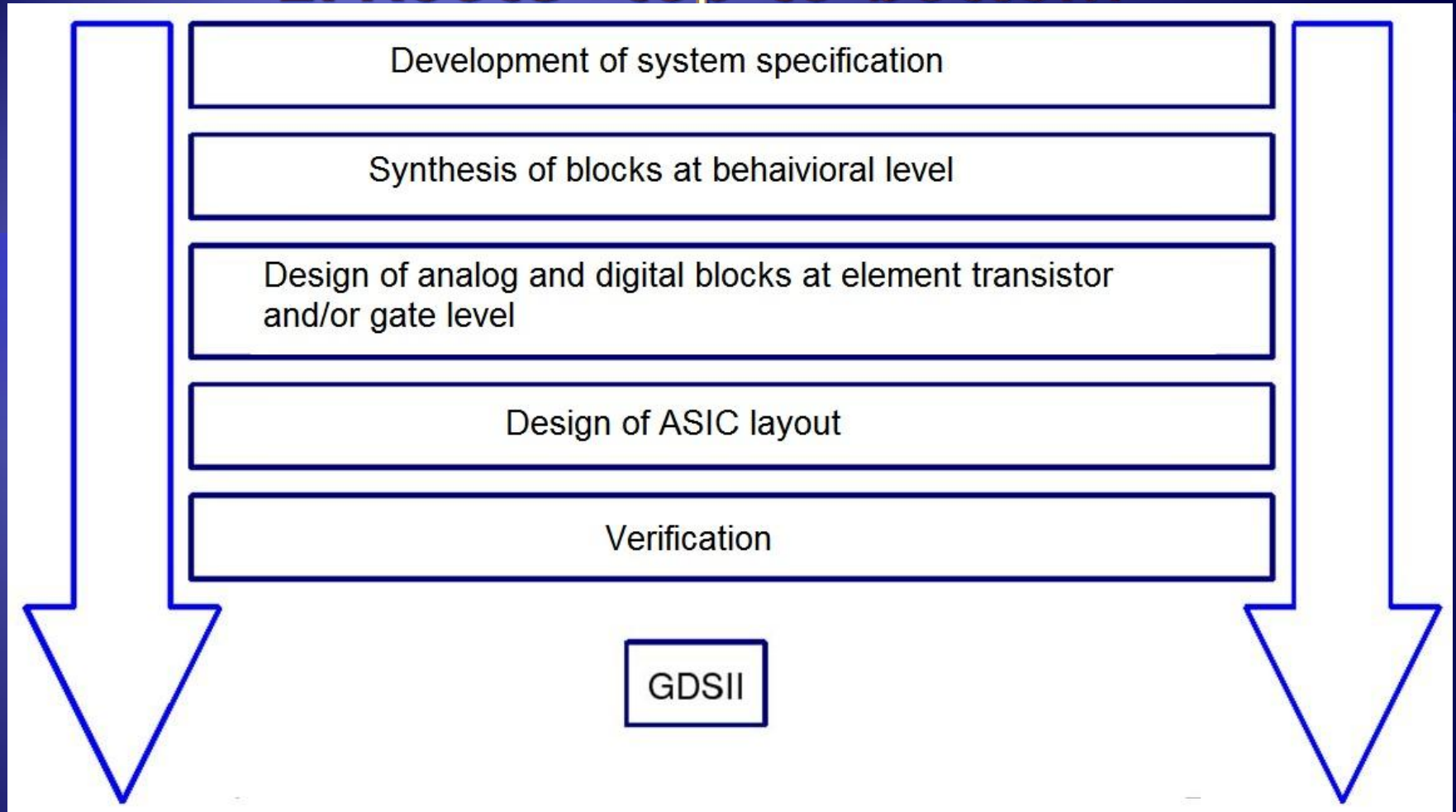
- ◆ Phase I: Design of analog and mixed-signal ASICs
- ◆ Phase II: Prototyping and test technique development
- ◆ Phase III: First tests and prototype characterization
- ◆ Phase IV: Qualification of ASICs
- ◆ Phase V: Preparation for a batch production and testing automation

1. Route «bottom-to-top» (traditional)



Feature: the possibility to perform a mixed-signal simulation for analysis of blocks interaction appears only after the all separate blocks being ready

2. Route «top-to-bottom»



Feature: the usage of mixed-signal simulations at early stage. Due to system synthesis at structure level, it becomes possible to develop fastly the block descriptions at behavioral level – RTL-Verilog, Verilog-A и Verilog-AMS. The same level of abstraction is available with VHDL

General principles of mixed-signal design

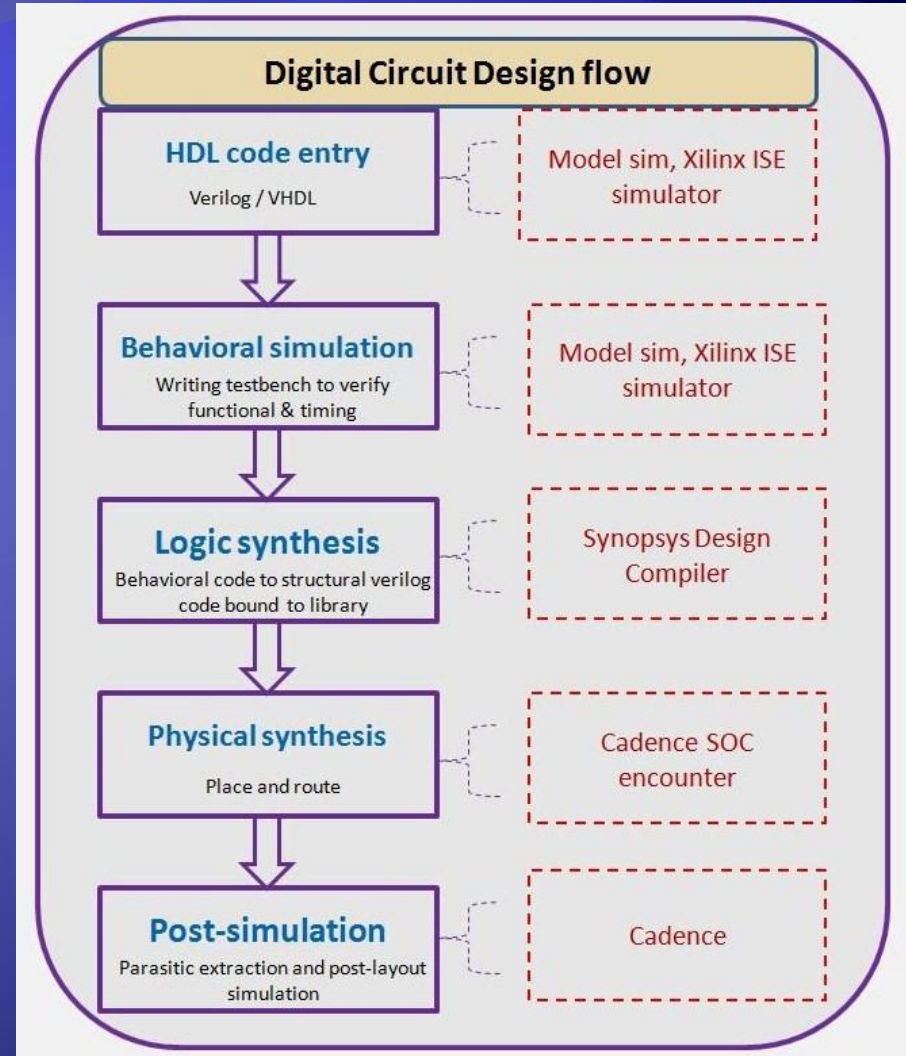
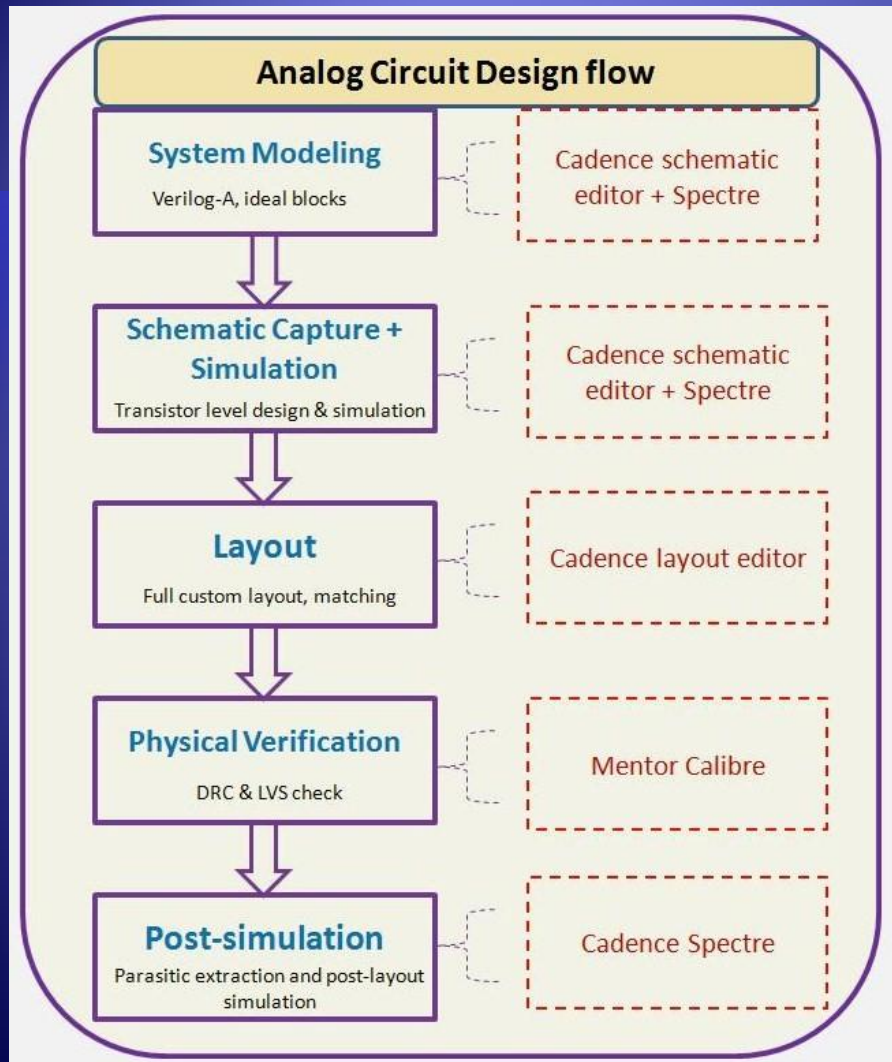
Modern ASICs, as a rule, are **mixed-signal** chips. They surely include both analog and digital parts

Analog part is designed as a custom block, whereas the digital one is described by VHDL or Verilog and then synthesized as a semicustom block, based on standard digital libraries

Now a system simulation at element (transistor) level requires unacceptably a lot of time

Usage of high description languages and software tools for **hierarchy** design allows to perform simulation with **different abstraction** level of blocks

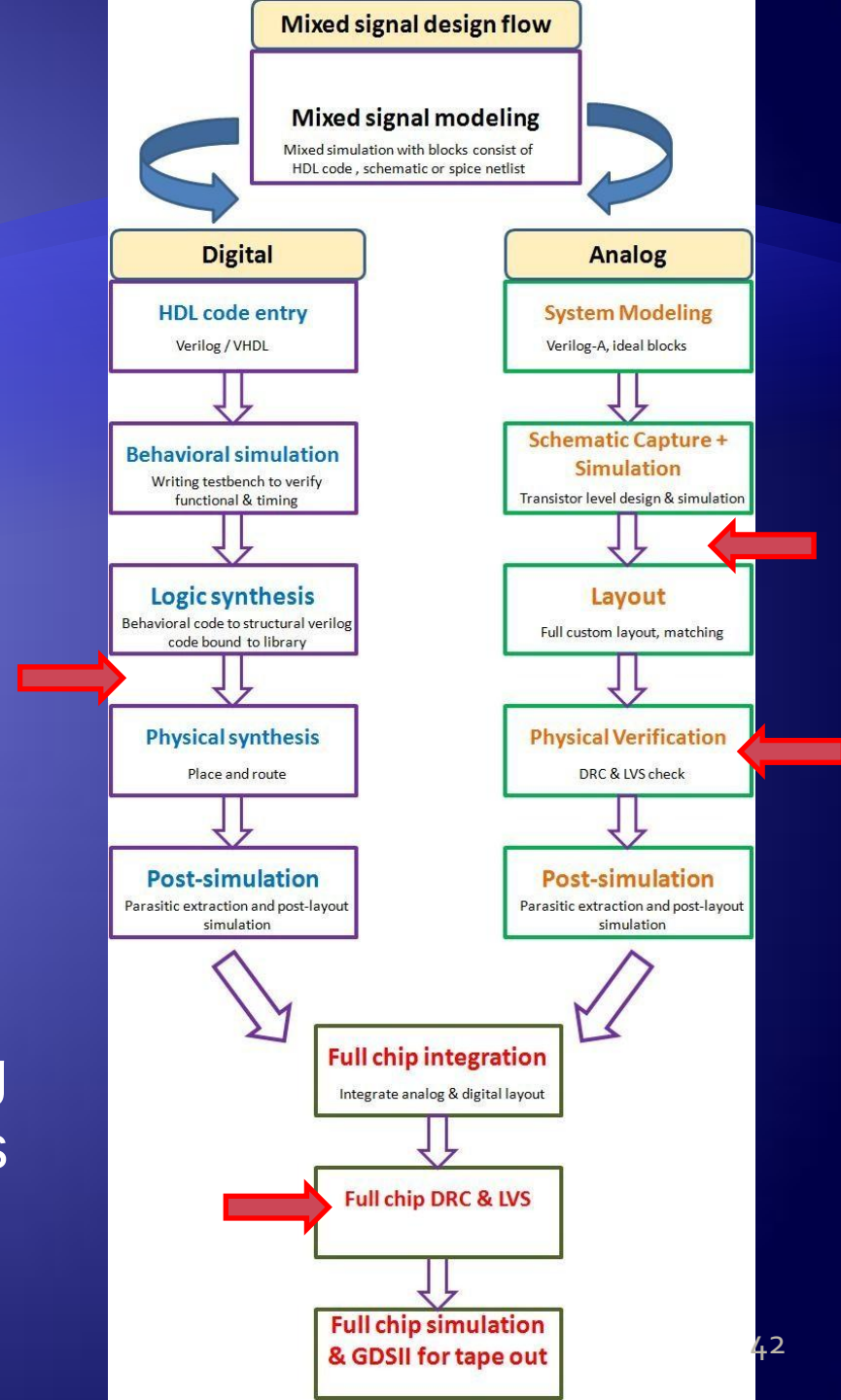
Traditional design routes



Routes for mixed-signal design

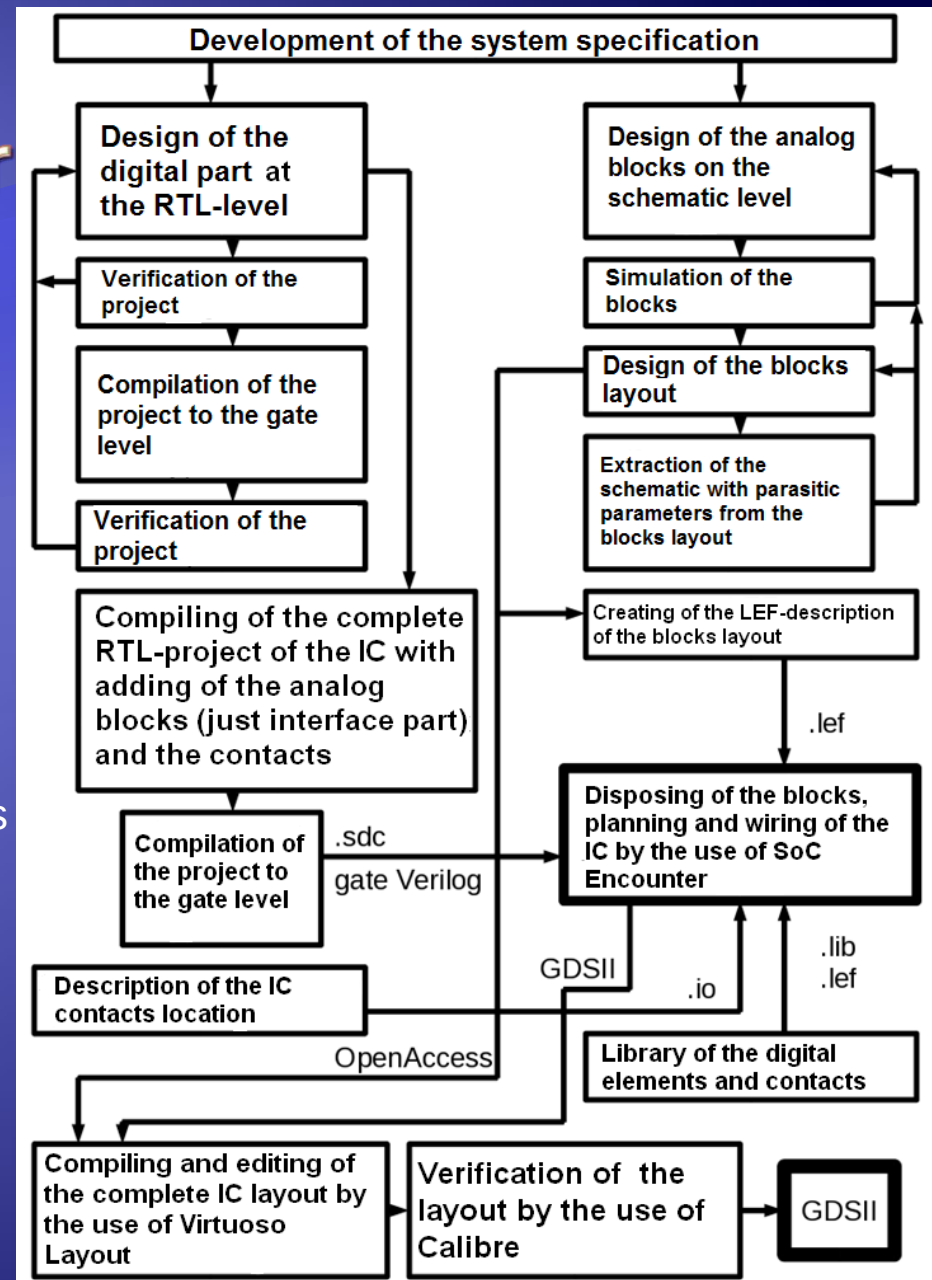
Usage of high description languages and software tools for **hierarchy** design allows to perform simulation with **different abstraction** level of separate blocks

➡ Design aspects, taking into account the requirements on radiation hardness

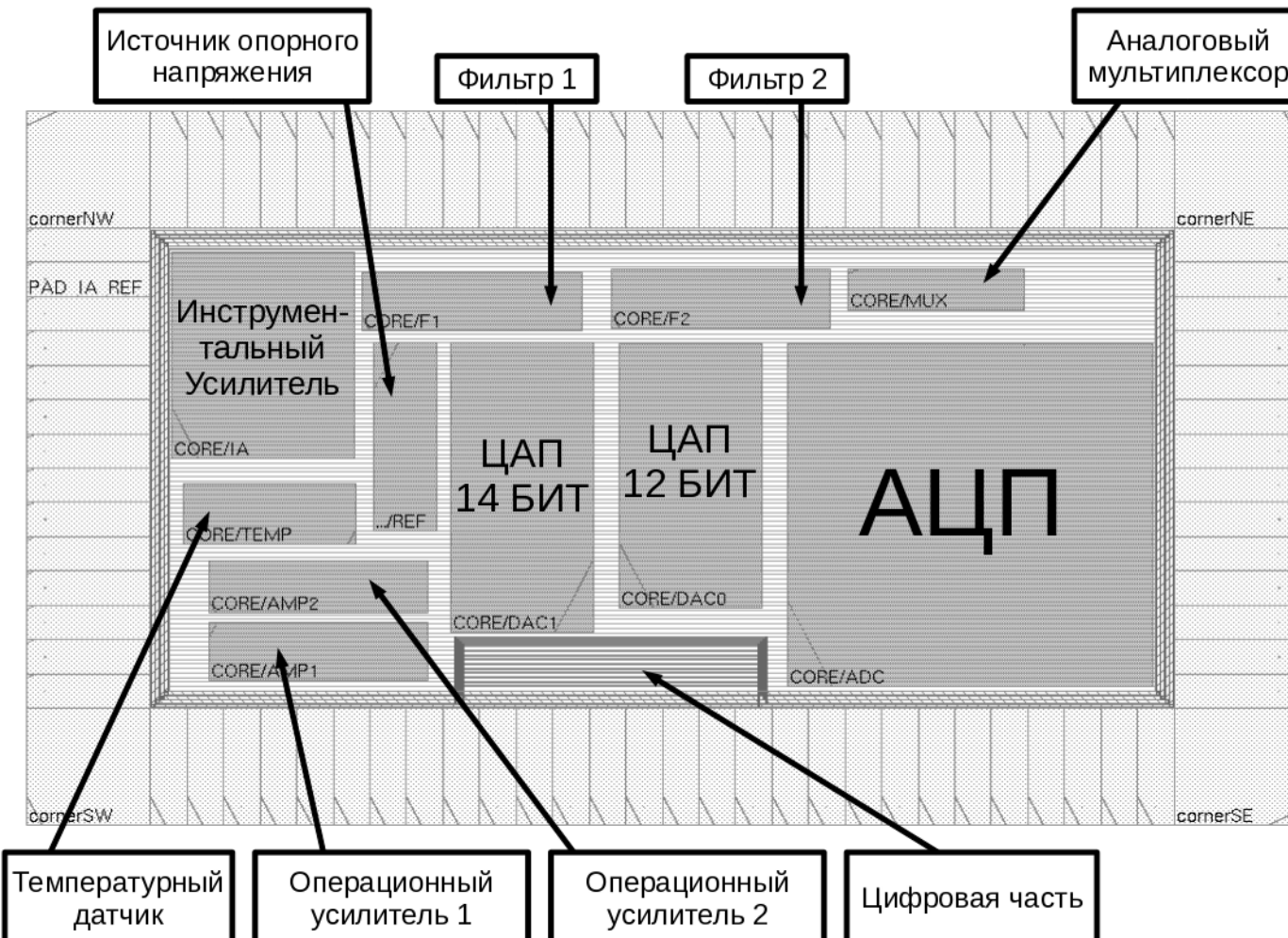


Example route for a smart pressure sensor readout ASIC

- Verilog description of whole ASIC
- Analog blocks are described as digital modules without functions, but with interface part
- Project compilation in gate level verilog
- For debugging it is necessary to have layout views of both standard library elements and analog blocks in format LEF (library exchange format)
- Few next stages are made in SoC Encounter, namely: placement of analog blocks, placement of digital part, routing of power supply buses, routing of signal wires



Smart pressure sensor readout ASIC

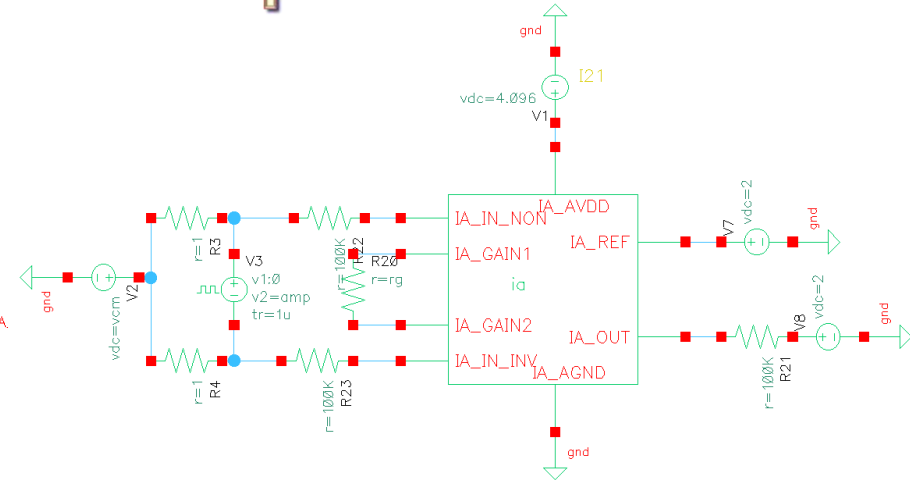
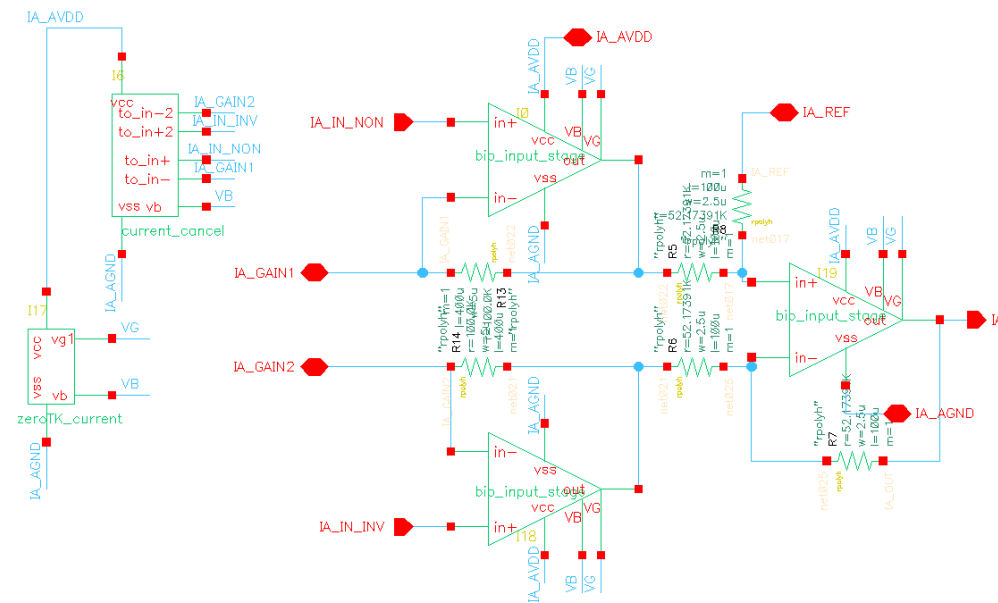


**Customer –
Rosatom**

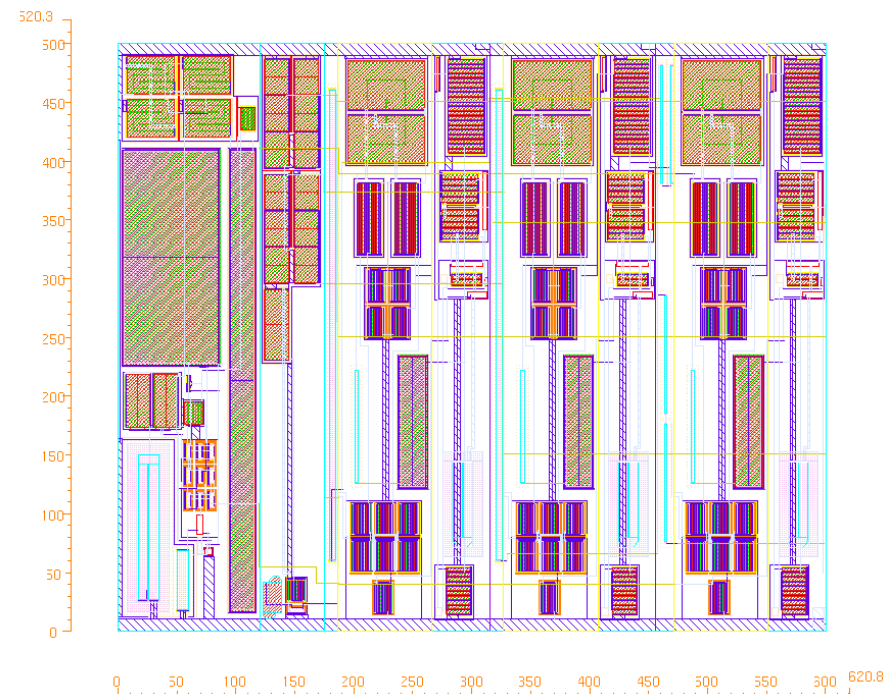
**Design duration –
8 months of 2010**

Chip planning in SoC Encounter (Cadence)

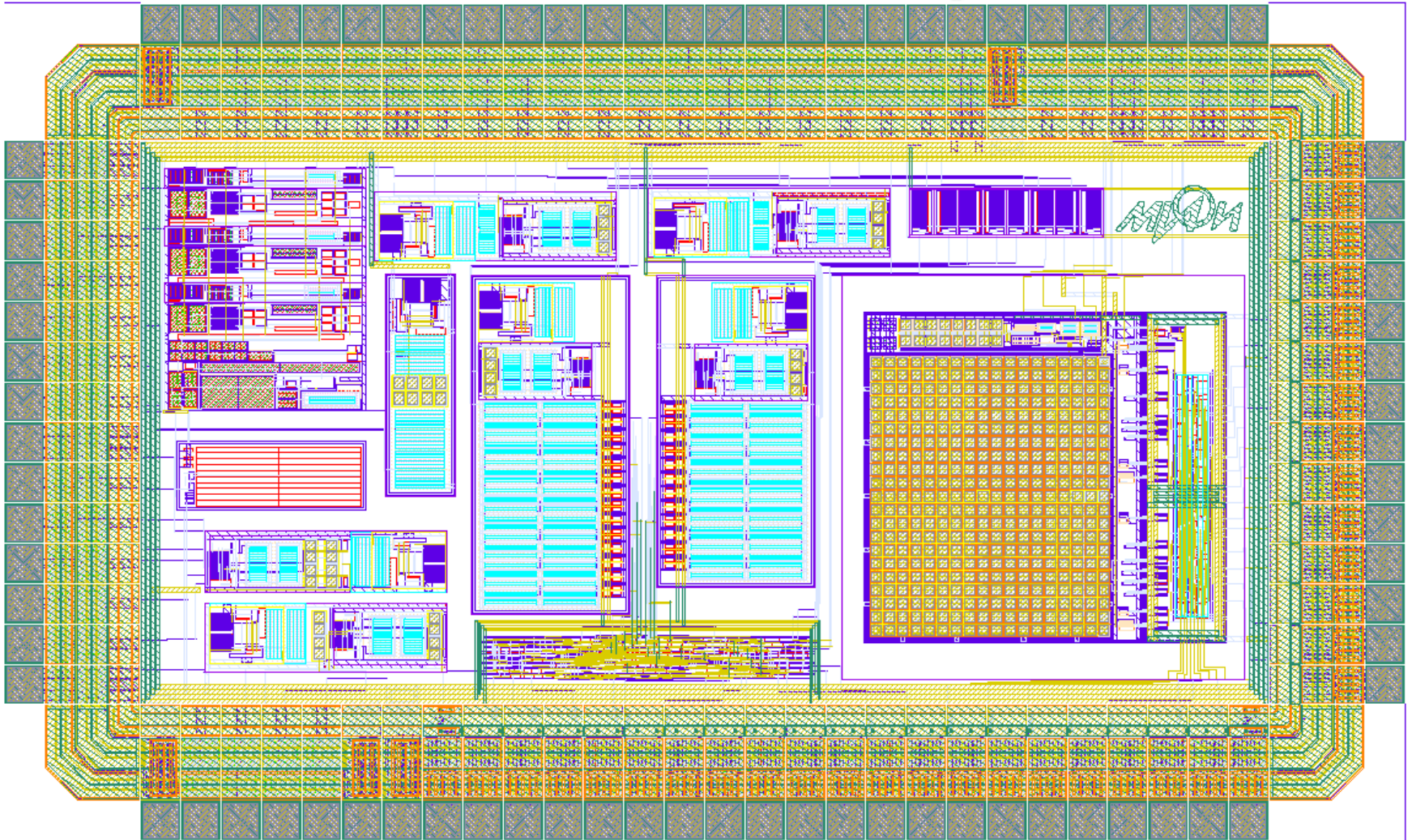
Instrumentation amplifier



Name	IA specs
Opamp gain	96 dB
Unity gain frequency	2 MHz
Phase margin	70 degree
Consumption current	100 μ A
RMS noise	20 nV/Hz ^{1/2}
Temperature range	-55...+80 °C
Input current	5 nA
Offset voltage	100 μ V

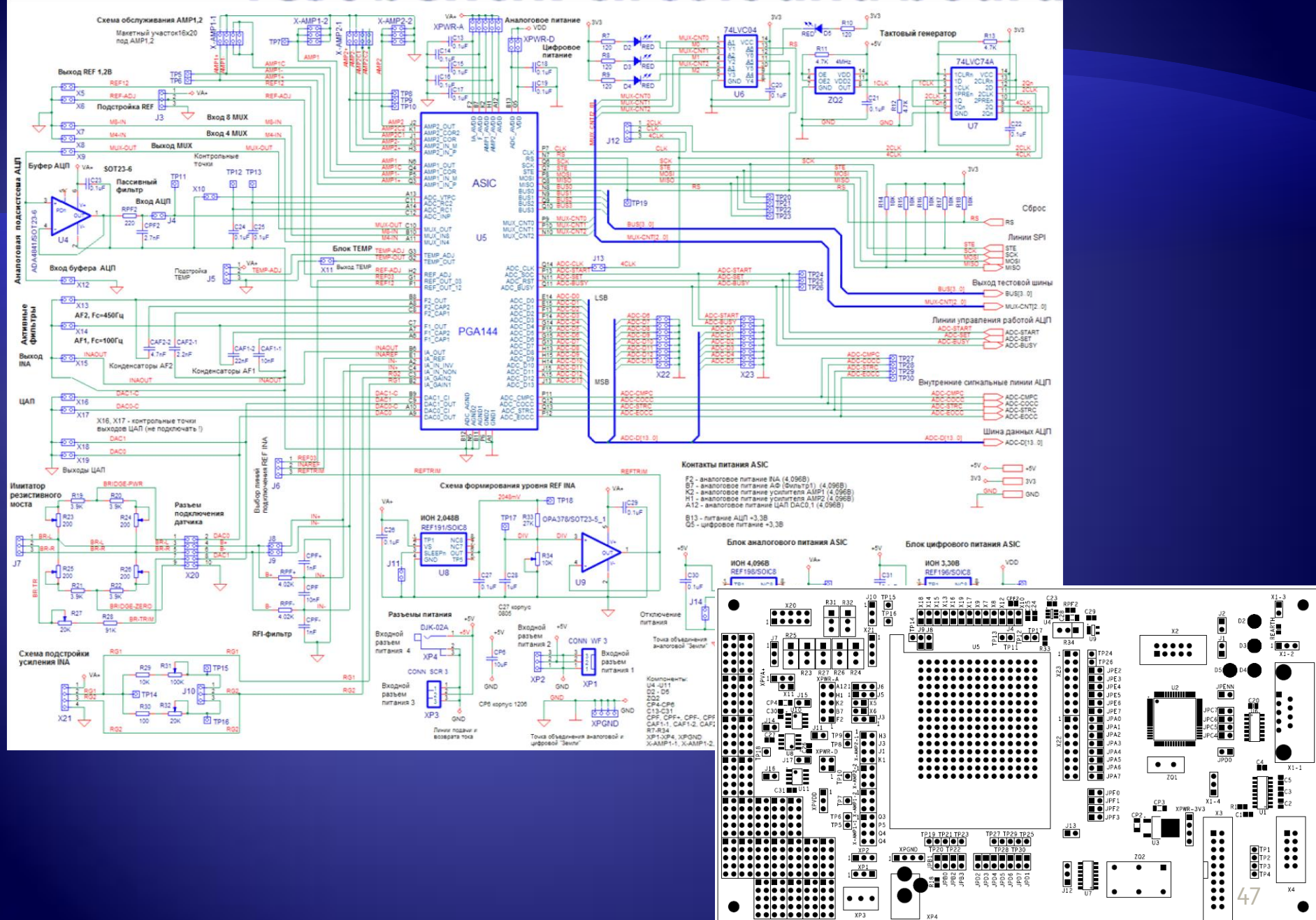


Smart sensor ASIC layout

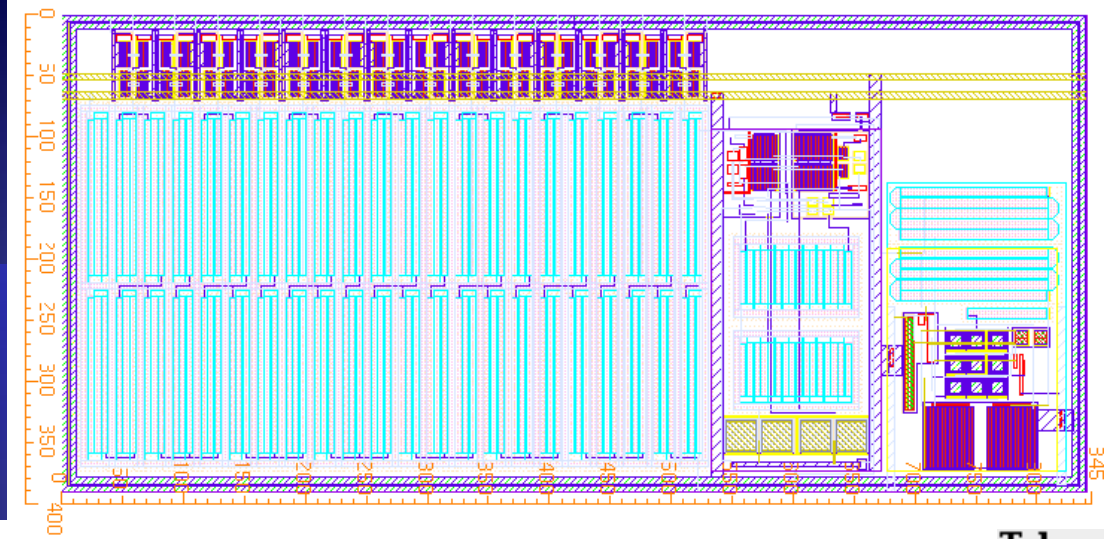


SiGe 0.35 μm BiCMOS of AMS

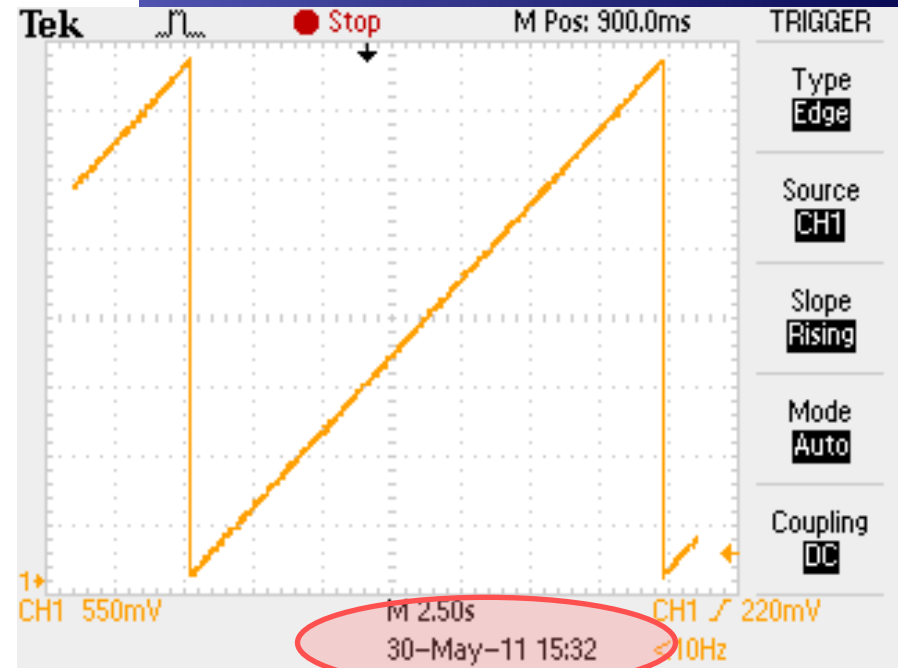
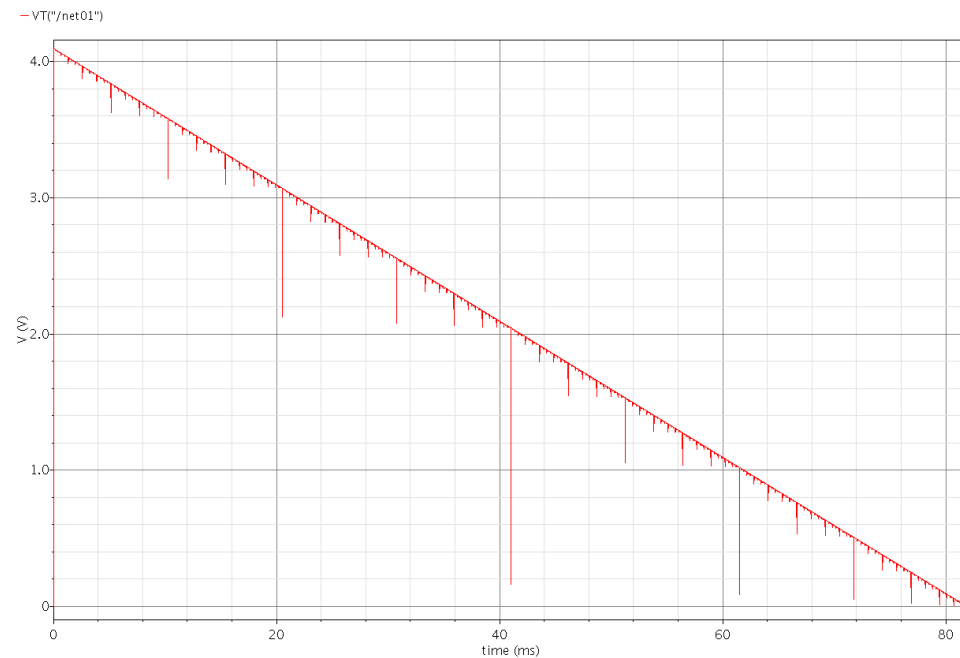
Test bench: circuit and board



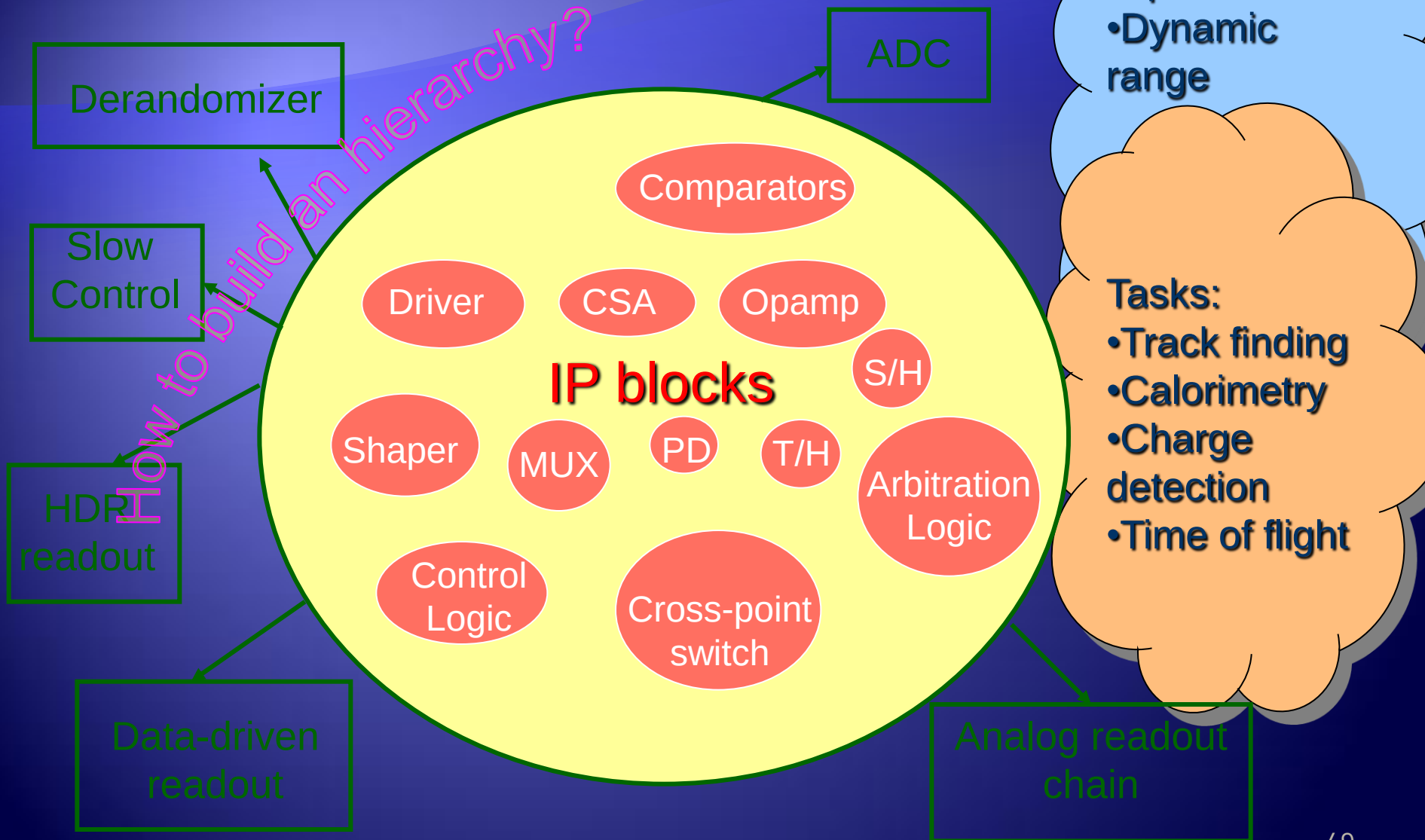
14-bit DAC



Name	DAC1
Number of bits	14 bits
Output range	3,9 V
Differential nonlinearity	1 LSB
Integral nonlinearity	2 LSB
Consumption current	80 μ A



Library of reusable IP blocks

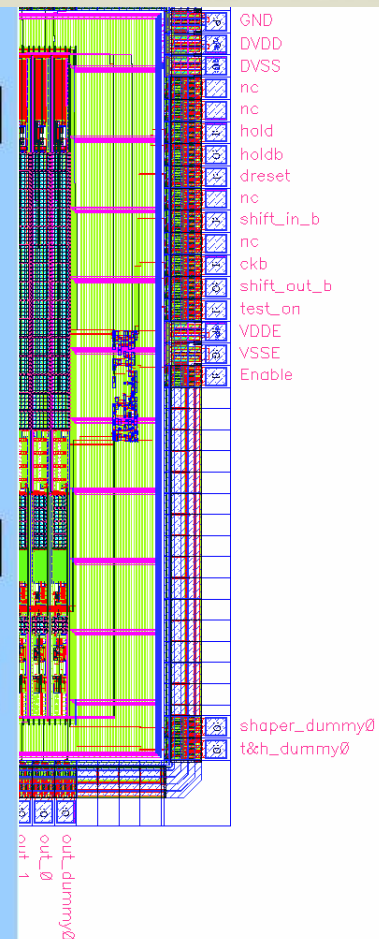
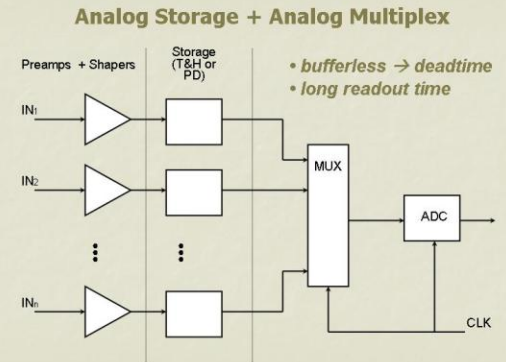


ASIC for Nucleon project*

- Большой динамический диапазон (100pC), потребление 2mW/ch, 32 канала
- Период проектирования 2005-2009
- AMIS 0.35 μ m CMOS
- 6 итераций:
 - 1) Analog, 16 CSAs (включен в отчет Europractice 2005г.) фев 2005
 - 2) Mixed-signal, 4+2(тест.) CSA+SH+T&H+MUX+Driver сент. 2006
 - 3) Mixed-signal, 4+2(тест.) CSA+SH+T&H+MUX+Driver фев. 2007
 - 4) Mixed-signal, 32+2 (тест.) CSA+SH+T&H+MUX+Driver апр. 2007
 - 5) Mixed-signal, 32+2 (тест.) (включен в отчет Europractice 2009г.)
CSA+SH+T&H+MUX+Driver сент. 2009
 - 6) Мелкосерийное производство. Mixed-signal, 32+2 (тест.)
CSA+SH+T&H+MUX+Driver апр. 2012
- Late 2014 ASIC has been launched from Baikonur to the Space

* ROSCOSMOS project

ASIC Structure



References

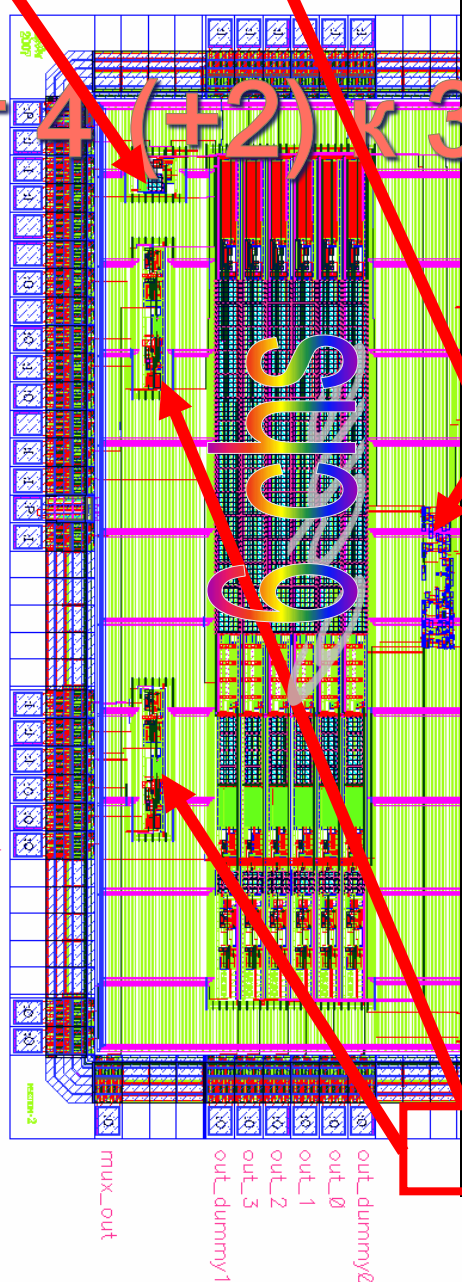
Digital part

От 4 (+2) к 32 (+2) каналам

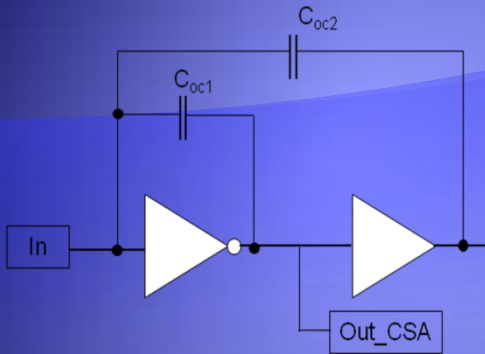
34chs

34chs

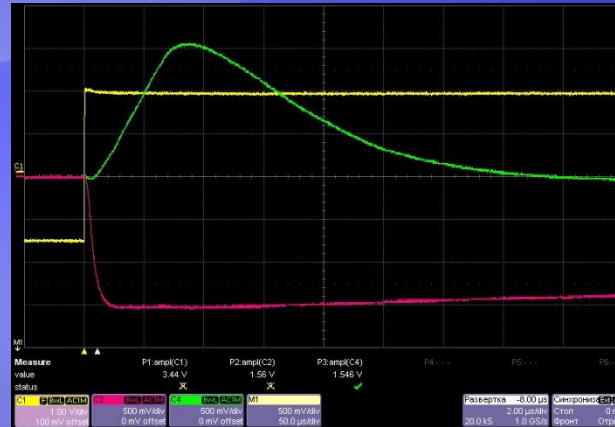
Differential Current drivers



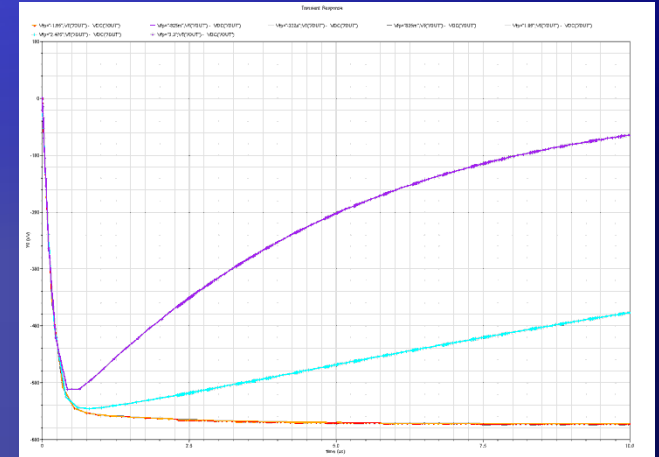
Scope diagrams



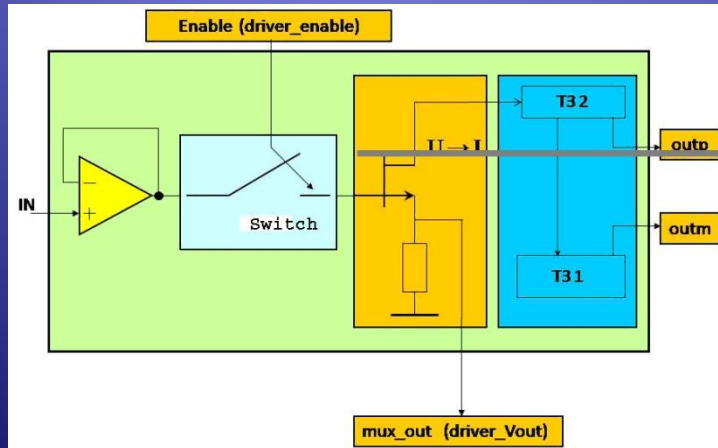
CSA structure



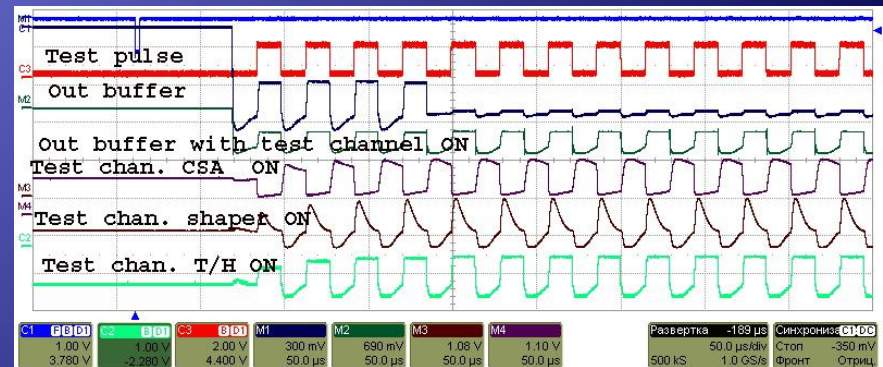
CSA/shaper response



CSA tail adjustment



Output current driver



Typical waveforms

Some relevant references

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http://www.itrs.net/Links/2009ITRS/2009Chapters_2009Tables/2009_ExecSum.pdf
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3. A.Marchioro, Can HEP Afford Private MPW Runs in the Future? // Proc. 5th international meeting on Front End Electronics for High Energy, Nuclear, Medical, and Space Applications, Colorado, 2003 http://www-ppd.fnal.gov/EEDOffice-w/conferences/FEE_2003/FEE2003talks/E4_Marchioro.pdf
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5. R. Lacoë, Improving Integrated Circuit Performance Through the Application of Hardness-by-Design Methodology IEEE Transaction on Nuclear science, v. 55, N4, 2008, p.1903-1925
7. K.Roy, B.Jung, A.Raghunathan, Integrated systems in the more-than-Moore Era: Designing lowcost energy efficient systems using heterogeneous components/ 23rd International Conference on VLSI Design, 2010

Conclusions

The future of instrumentation is tightly bound with a wide usage of **ASICs** due to the new challenge in integration scale

The solution of **system** (architectural, structural) problems will demand substantially higher efforts. Actually there is the question of creating not separate components, but whole systems on chip (**SoC**)

Almost all new chips have a **mixed-signal character**

Nowadays the design is based on microelectronic **CADs** and the adapted **Design Kits** of the chosen manufacturer

Reduction of timelines for design, extension of reusable IP block libraries, new level of **system tests** for readout electronics – all of that requires the usage of advanced CAD in distributed fast networks of powerful computing clusters

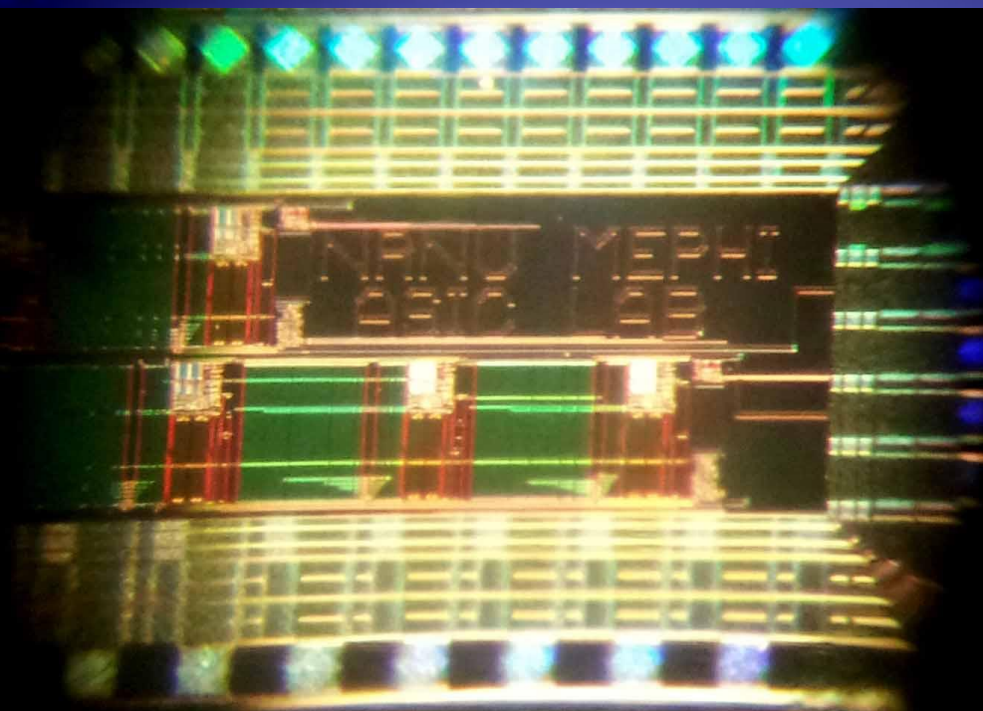
Conclusions (2)

The **“Rad-hard by design”** approach for commercial CMOS technology is considered to be the best way of providing an **acceptable** rad-hardness by circuit and layout techniques.

For rad-hardness and temperature stability of the chips it is important to refine the existing libraries and design routes

Long term planning becomes an extremely important factor, especially taking into account the “life time” of both the chosen technology and the design staff

The necessity of a **wider collaboration** between the design centers and research institutions, sharing the process of preparing human resources and the cost of using expensive CAD



Спасибо за
внимание

